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Nanostructured Materials to Negate Nanosecond Voltage Spikes

Simeon Gilbert

April 24th, 2024

Emergent Quantum Materials and Technologies
(EQUATE) Seminar

University of Nebraska – Lincoln



Focus Areas at Sandia National Laboratories



Global Security



Nuclear Deterrence



*National Security
Programs*



*Advanced Science &
Technology*



*Energy & Homeland
Security*





Granular Metal Team

PI: Laura Biedermann

Granular metal growth: **Simeon Gilbert**, Michael Siegal, Doug Vodnik, Lyle Brunke

Granular metal electrical characterization: Michael McGarry, Will Bachman, Peter Sharma, Tyler Bowman, Luke Yates

Microscopy and spectroscopy: **Simeon Gilbert**, Melissa Meyerson, Paul Kotula, Samantha Rosenberg, Tommy Kmiecik

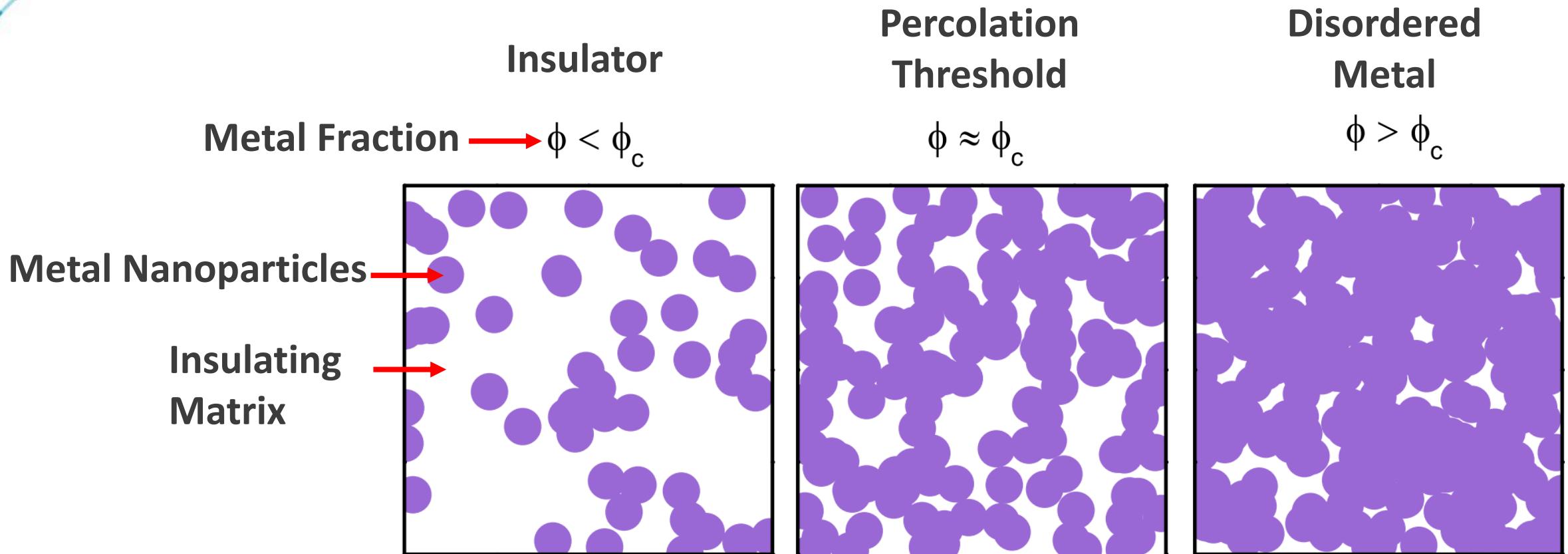
Device and PCB design: Jack Flicker, Rachid Darbali-Zamora, Will Bachman

Lithography and packaging: Patrick Finnegan, Scott Weathered, Adrian Cassias, Connor Healey, Alvin Ha



This work was supported by the Laboratory Directed Research and Development program at Sandia National Laboratories. Sandia National Laboratories is a multimission laboratory managed and operated by National Technology and Engineering Solutions of Sandia, LLC, a wholly owned subsidiary of Honeywell International Inc., for the U.S. Department of Energy's National Nuclear Security Administration under contract DE-NA0003525.

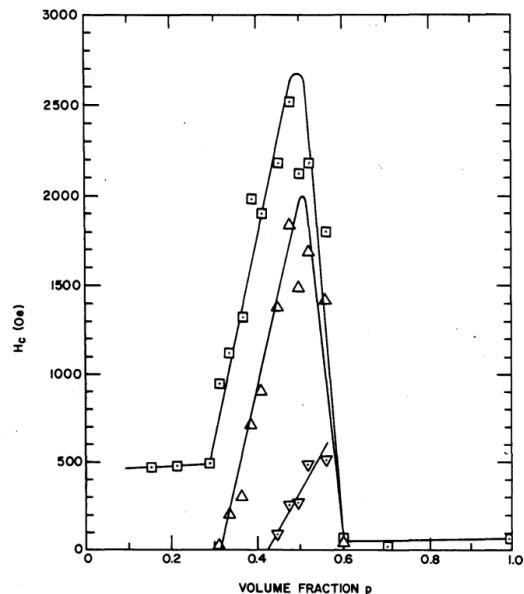
What are granular metals (GMs)?



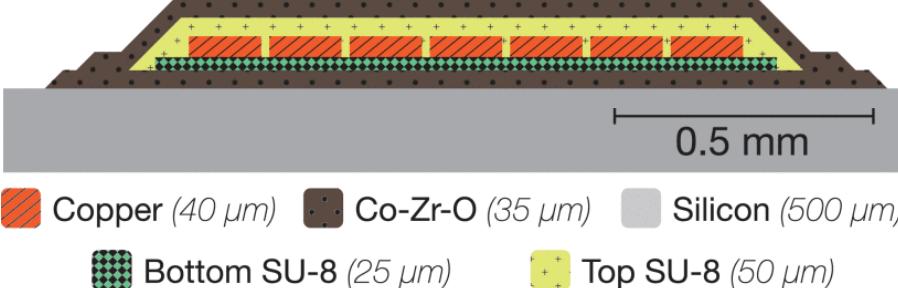
Grimaldi, Phys. Rev. B **89**, 214201 (2014)

Applications of Granular Metals

Magnetic Materials

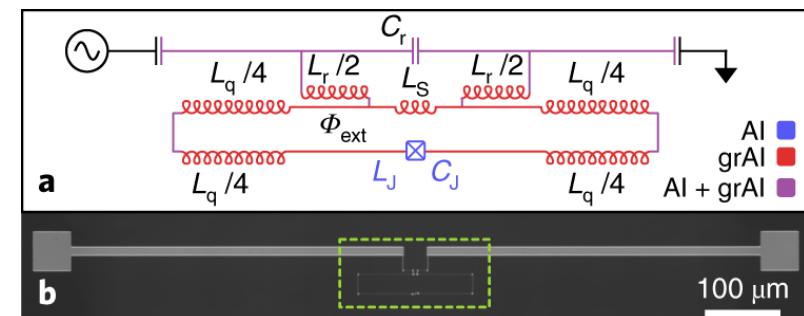


S. H. Liou and C. L. Chien; Granular metal films as recording media. *Appl. Phys. Lett.* **52**, 512 (1988)



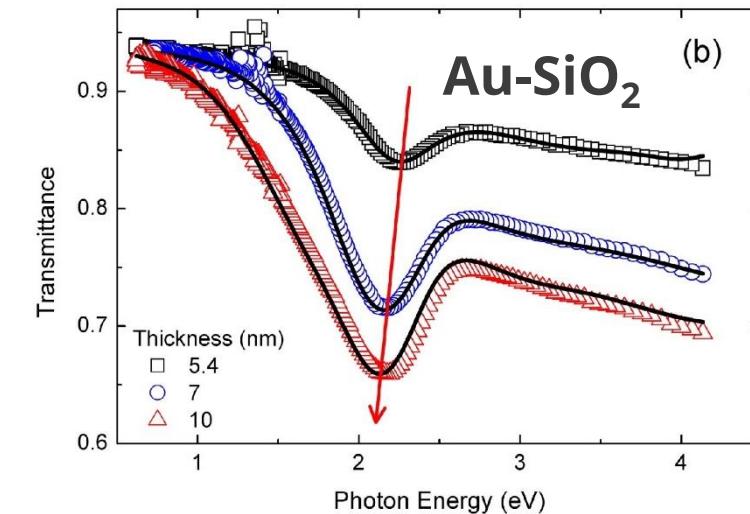
D. V. Harburg *et al.*, *IEEE Journal of Emerging and Selected Topics in Power Electronics* **6**, 1280 (2018)

Superconducting Circuits



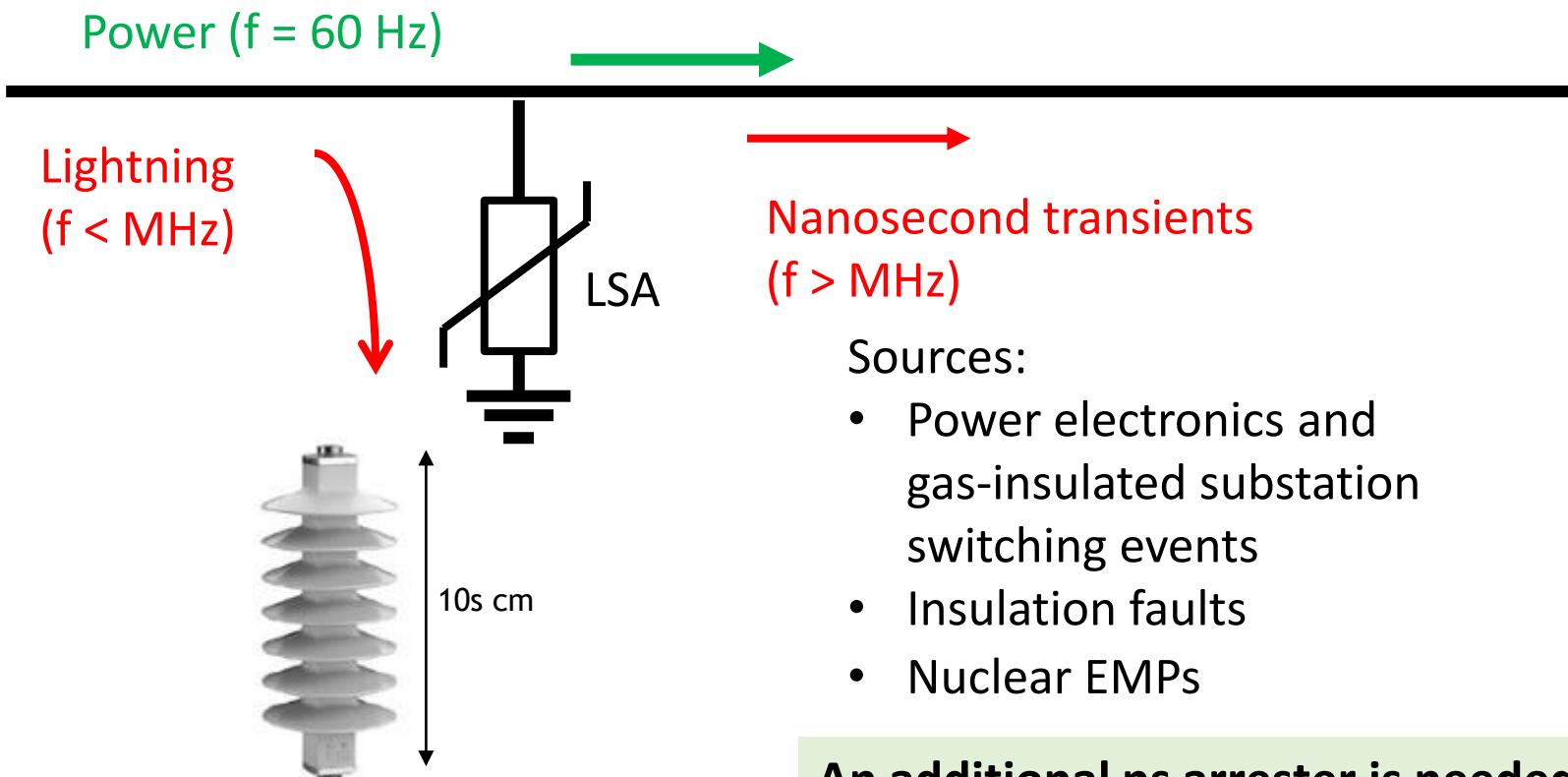
L. Grünhaupt *et al.*, *Nat. Mater.* **18**, 816 (2019)

Plasmonics



H. Bakkali, *et al.* *Applied Surface Science* **405**, 240 (2017)

Nanosecond high-voltage transients threaten electrical grid reliability



Lightning surge arresters' (LSAs)
response time is ~ 100 ns

Nanosecond transients
($f > \text{MHz}$)

Sources:

- Power electronics and gas-insulated substation switching events
- Insulation faults
- Nuclear EMPs

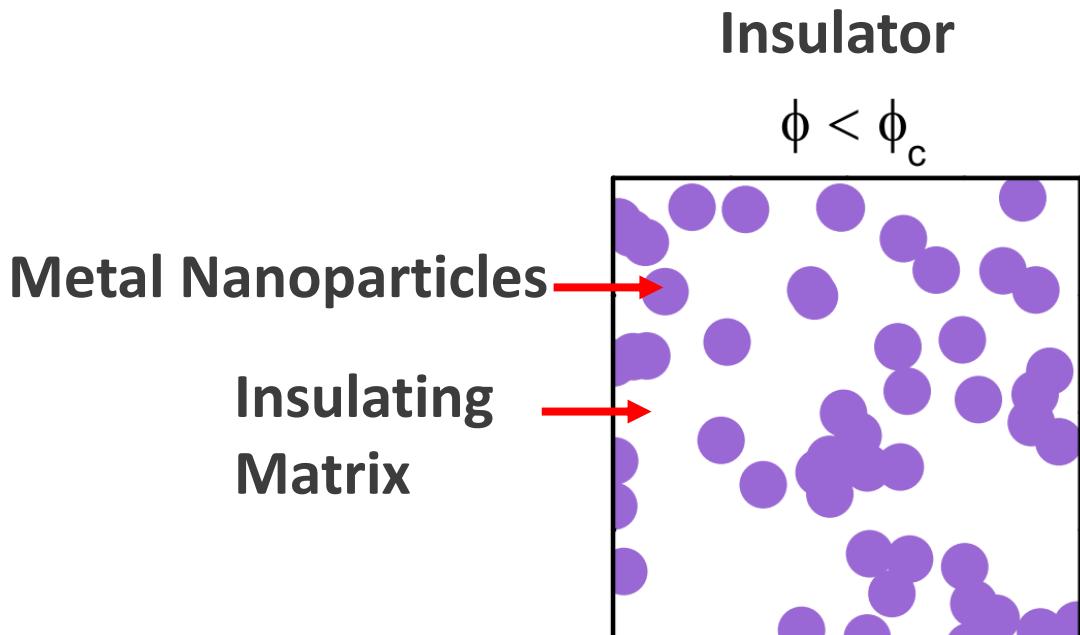
**vulnerable
infrastructure**



An additional ns arrester is needed with

- High breakdown strength for compact devices
- Low conductivity, σ , at grid voltages and frequencies
- High σ at MHz/GHz frequencies and with overvoltages
- High thermal stability
- Large current carrying capacity ($>1 \text{ kA/cm}^2$)

Granular metals are promising for ultrafast grid protection.



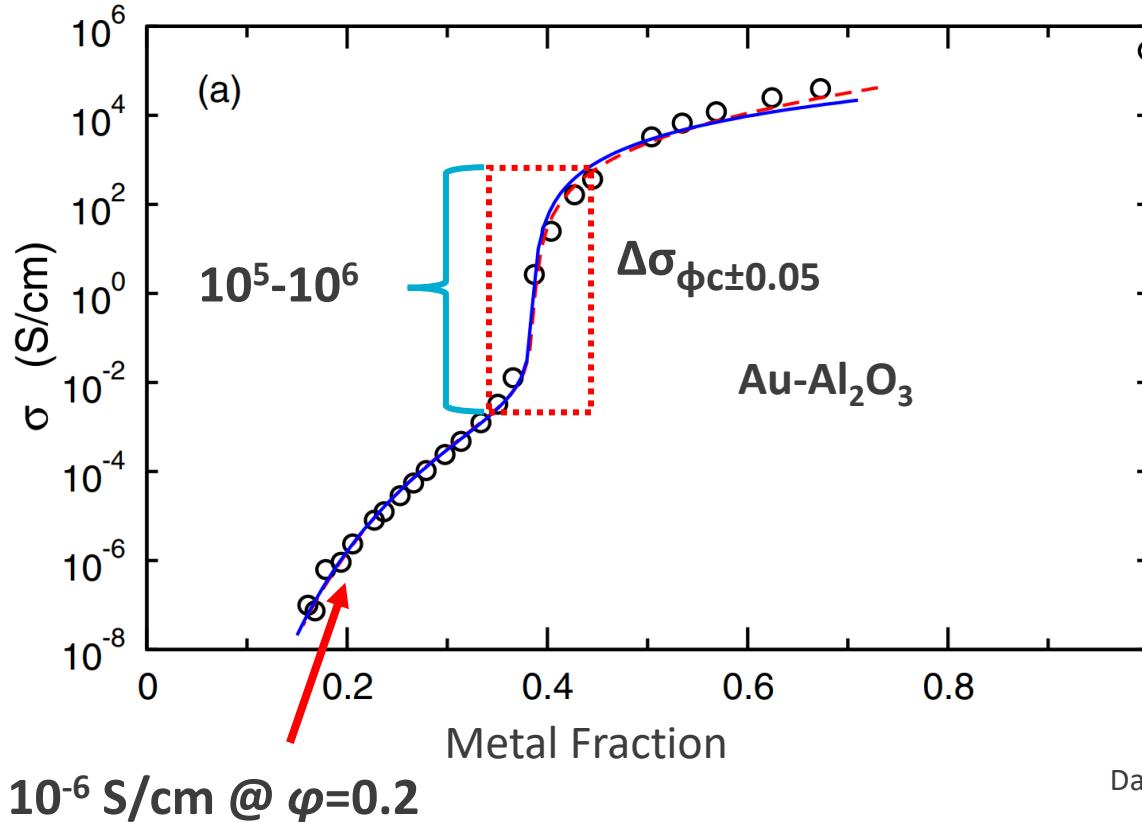
Grimaldi, Phys. Rev. B 89, 214201 (2014)

Below φ_c conduction occurs via electron tunneling and capacitive transport.

Conduction from electron tunneling increases at higher electric fields.

Conduction from capacitive transport increases at higher frequencies.

GMs have desired low DC conductivity.

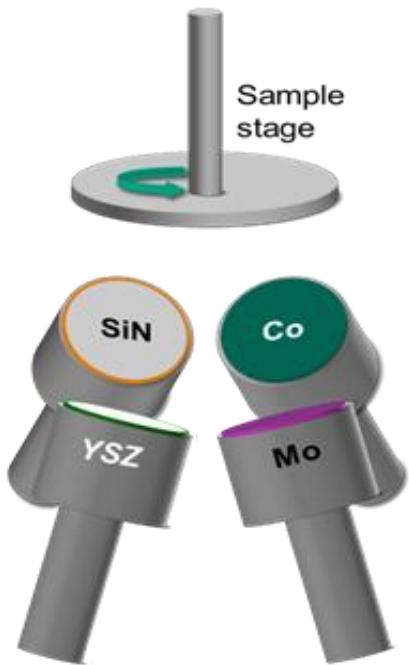


Data: Abeles et al. Adv. in Phys. **24**, 407 (1975)

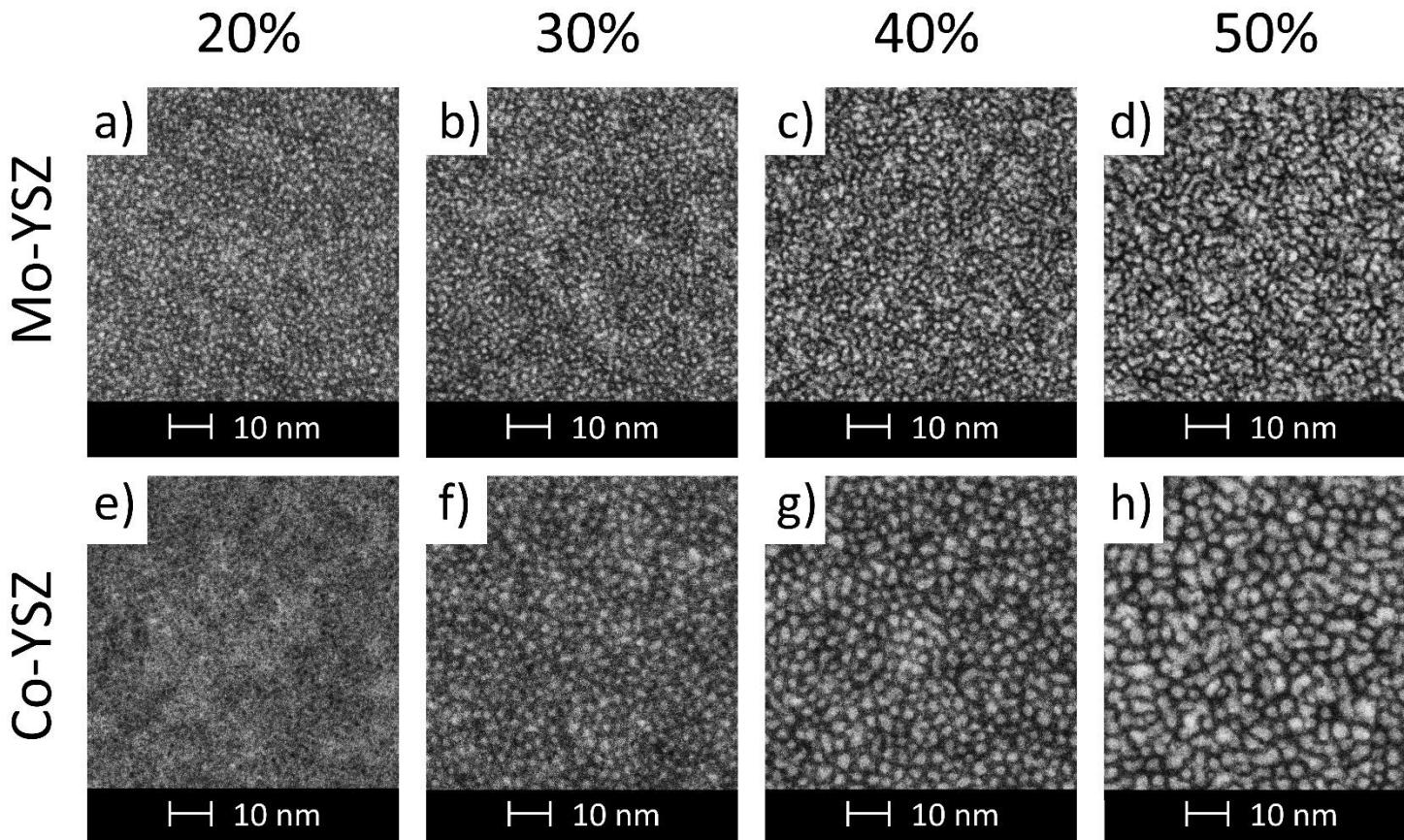
Figures: Grimaldi, Phys. Rev. B **89**, 214201 (2014)

Conductivities of $<10^{-5}$ S/cm are desired to reduce leakage currents.

Co-YSZ and Mo-YSZ synthesized by RF co-sputtering in Ar



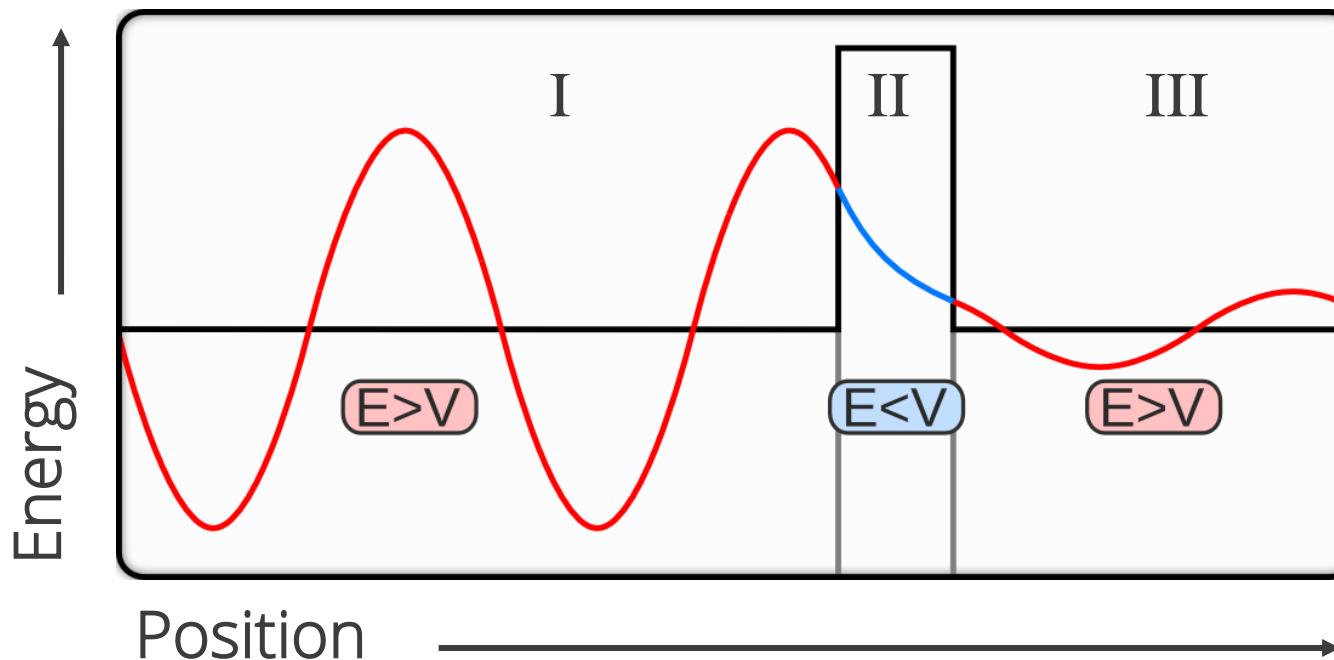
Volumetric Metal Fraction



Metal island diameters between 1-3 nm.

Particle separation distances are ~0.2 - 0.6 nm

Quantum Tunneling

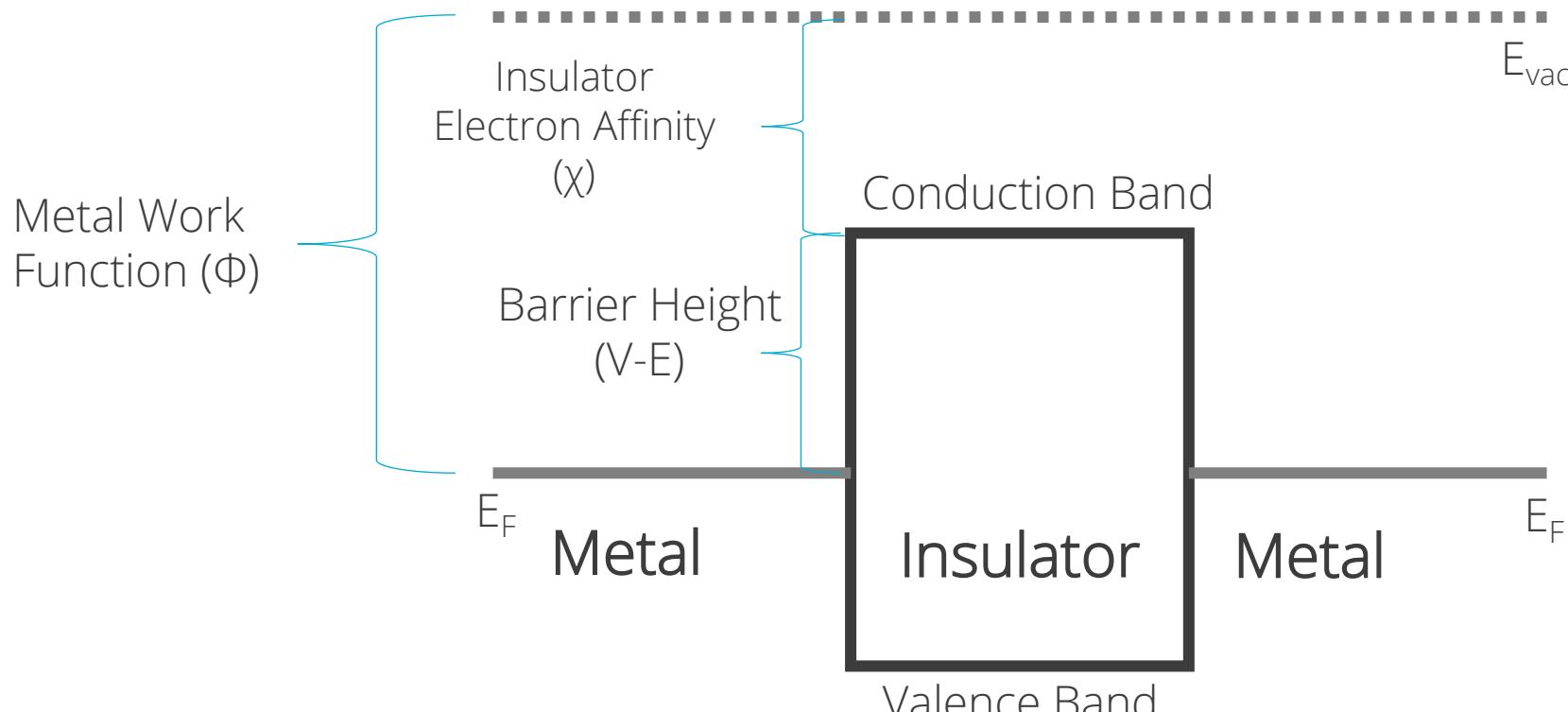


$$\Psi(x) = \begin{cases} Ae^{ikx} + Be^{-ikx} & , \text{ I} \\ Ce^{\kappa x} + De^{\kappa x} & , \text{ II} \\ Fe^{ikx} & , \text{ III} \end{cases}$$

Tunneling Probability Decay Length

$$\kappa = \sqrt{\frac{2m(V-E)}{\hbar^2}}$$

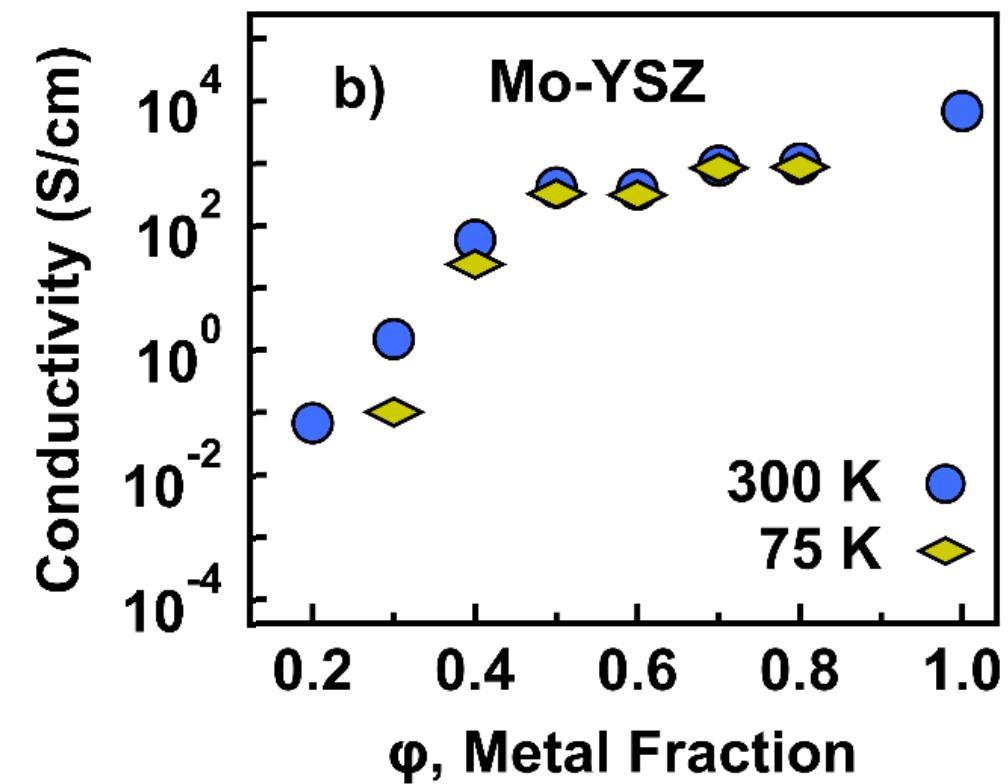
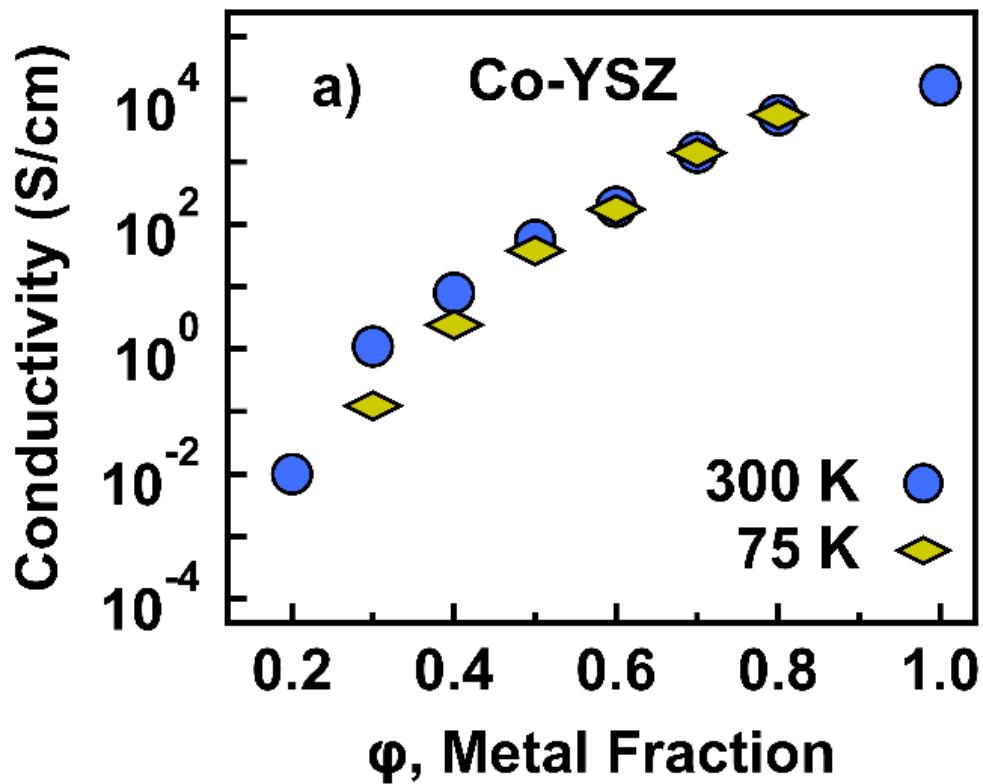
Quantum tunneling in granular metals



Tunneling Probability Decay Length

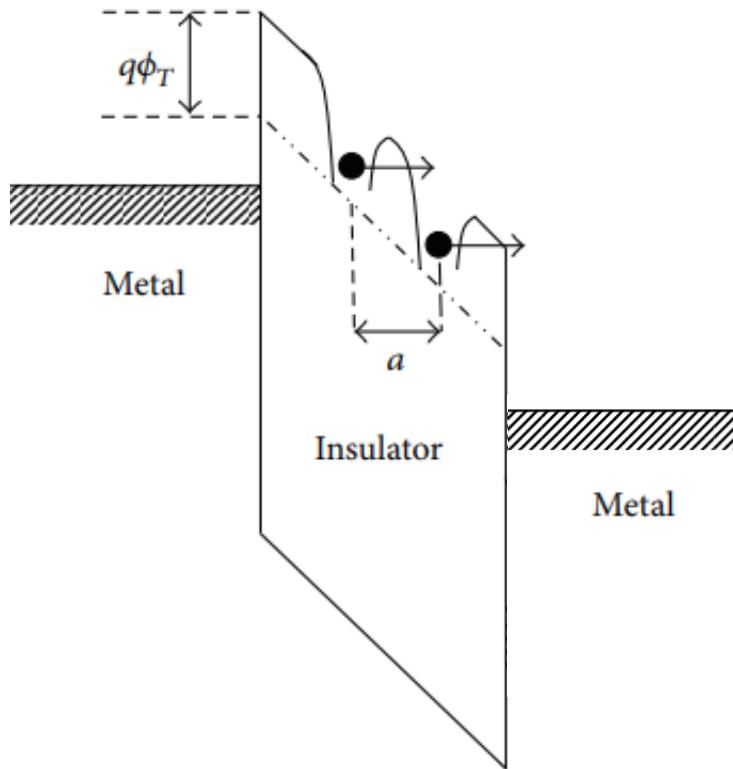
$$\kappa = \sqrt{\frac{2m(V-E)}{\hbar^2}} = \sqrt{\frac{2m(\Phi-\chi)}{\hbar^2}} = 0.1 - 0.2 \text{ nm}$$

Co-YSZ and Mo-YSZ have high DC conductivities.



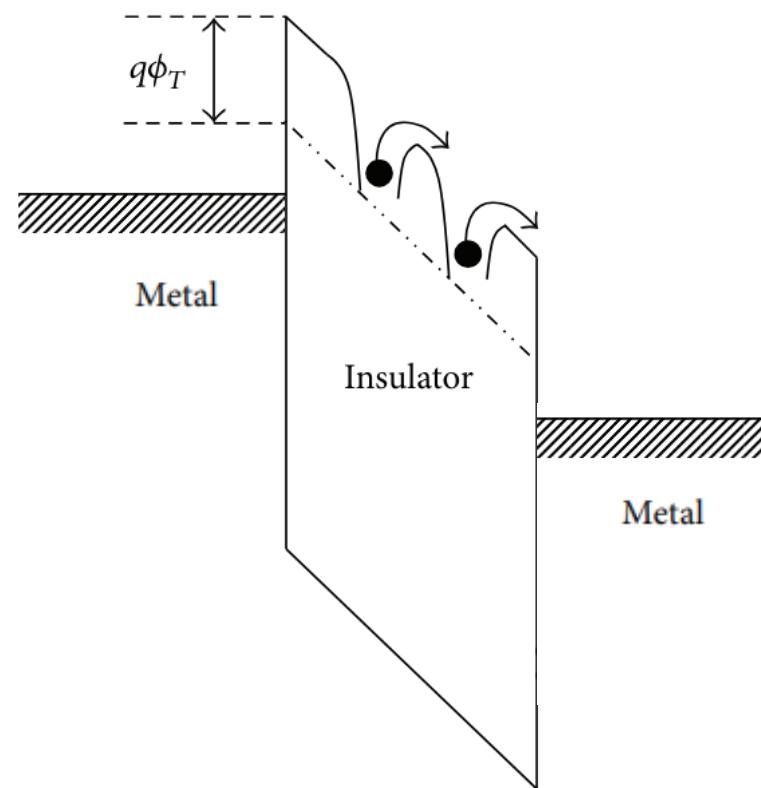
Potential tunneling mechanisms

Hopping Conduction



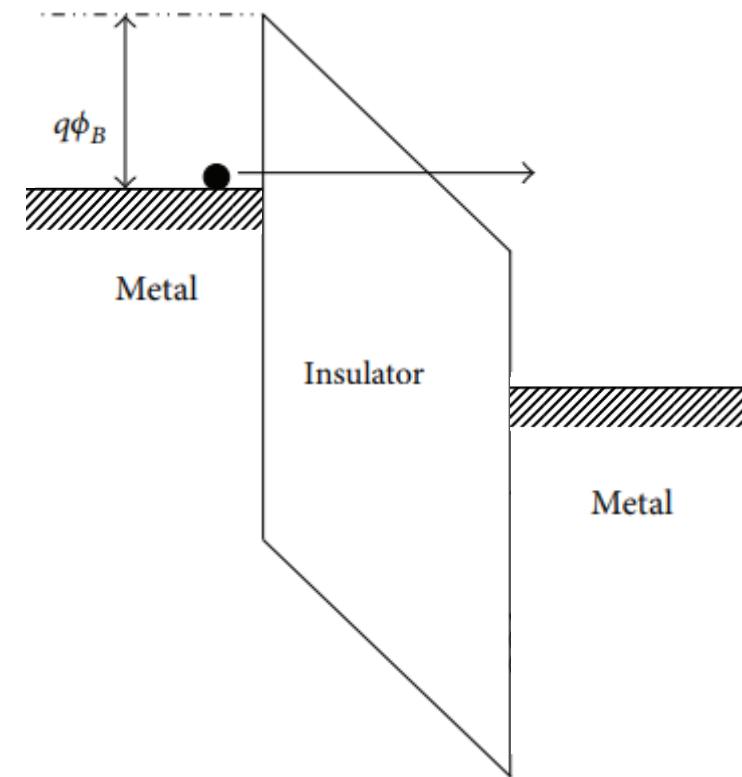
$$\sigma \propto \exp(-2\sqrt{E_A/k_B T})$$

Poole-Frenkel Emission



$$\sigma \propto \exp \left[(q/k_B T) \sqrt{qE/\epsilon_0 \epsilon_r} \right]$$

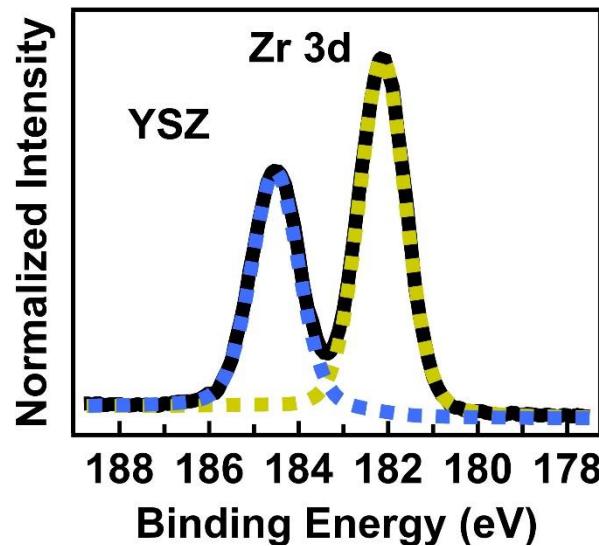
Fowler-Nordheim Tunneling



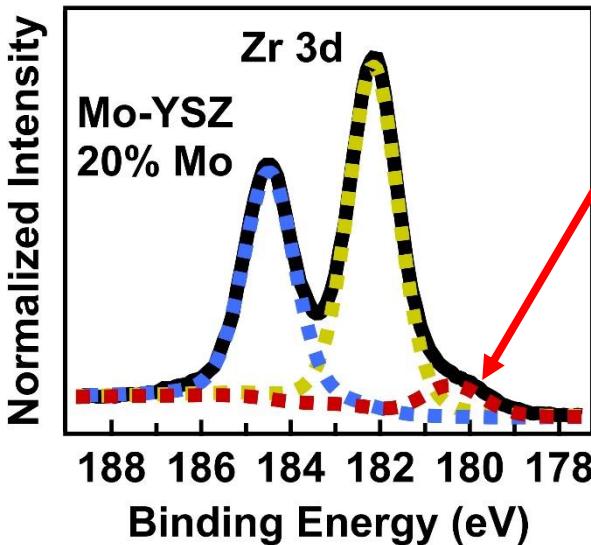
$$\sigma \propto E^2 \exp(E_0/E)$$

Conductivity depends on defect density, temperature and electric field.

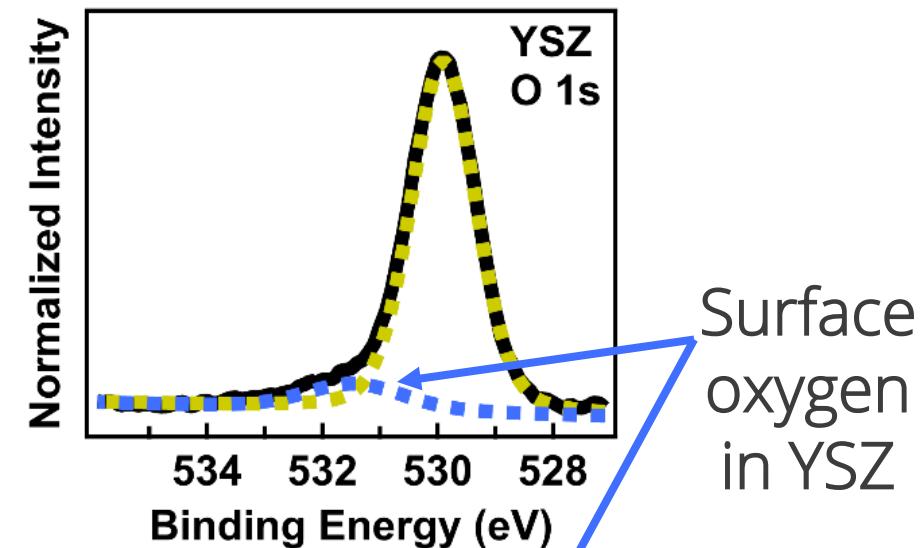
X-ray photoemission spectroscopy shows metal-oxide formation



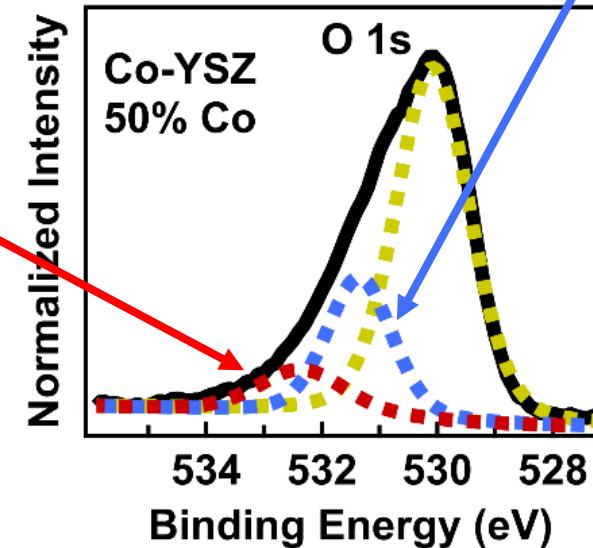
Zr^{2+} from
oxygen
vacancies



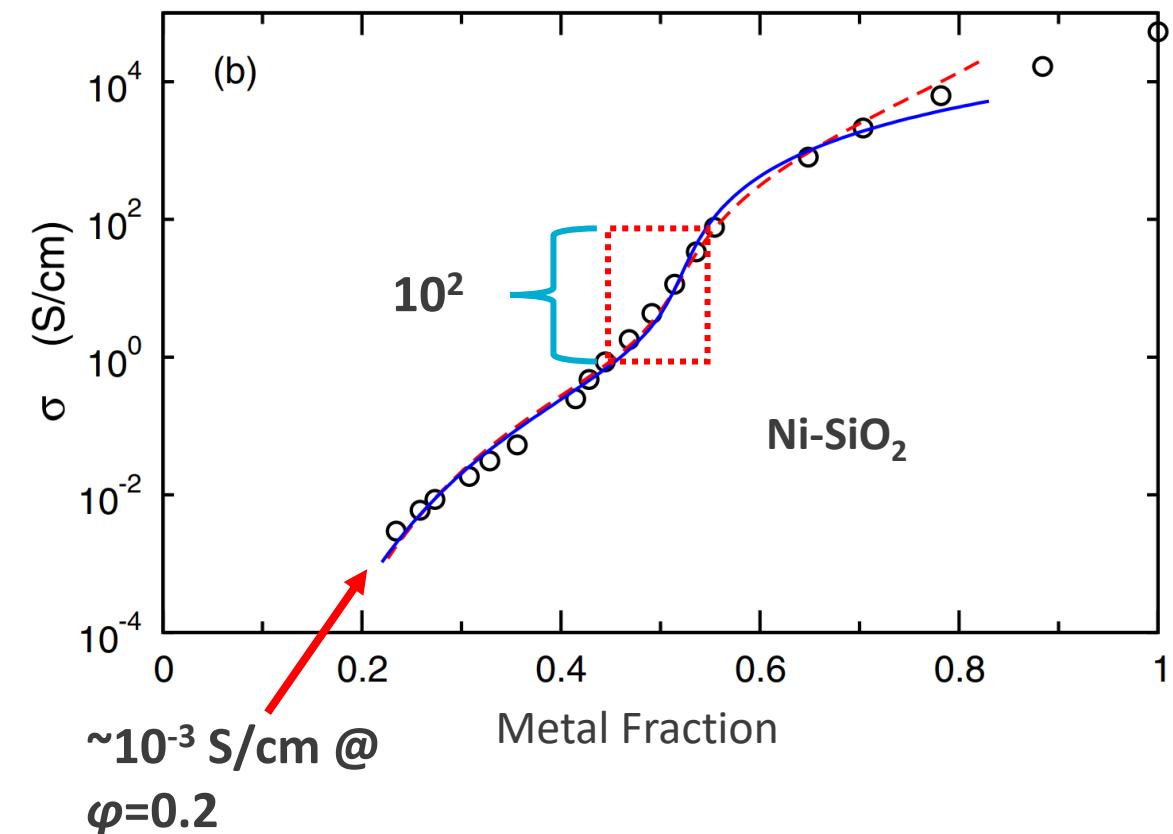
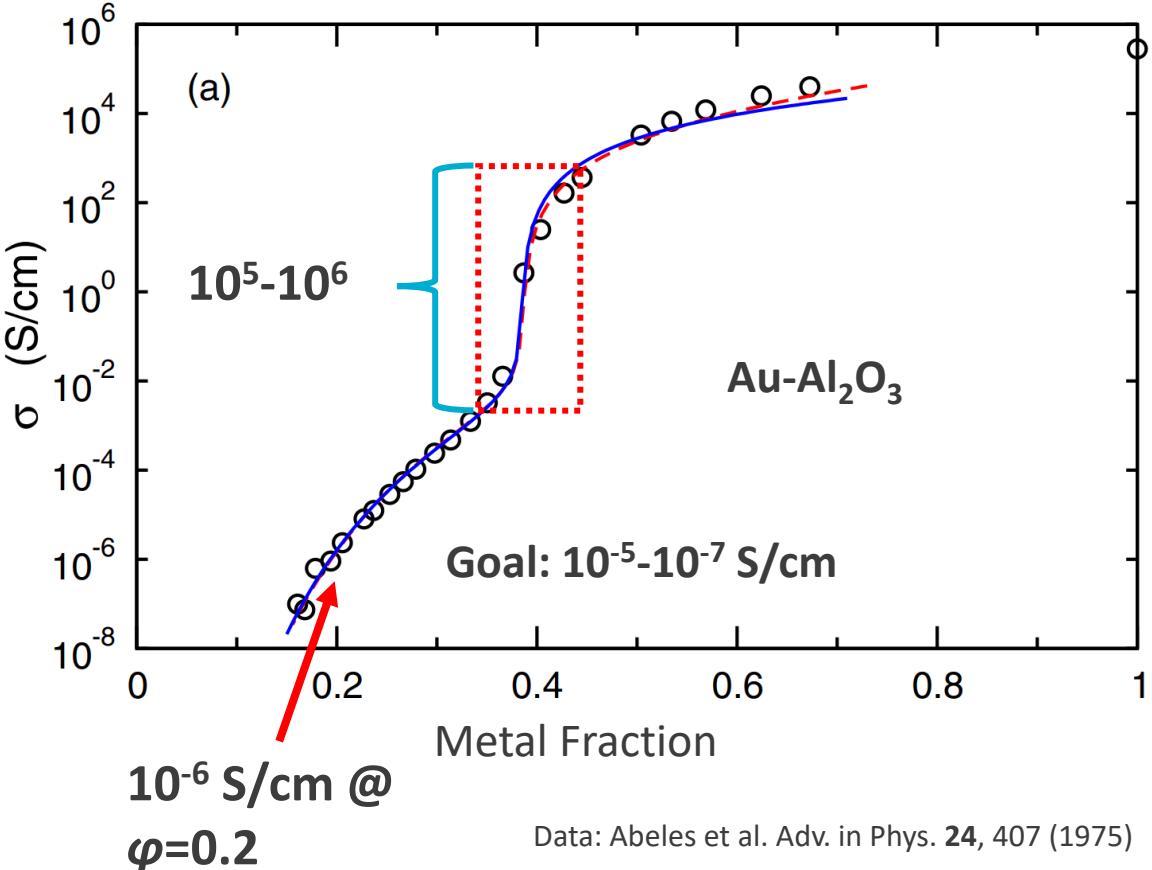
Metal-oxide
interface
states



Surface
oxygen
in YSZ



Noble Metal GMs have desired low DC conductivity.



Metal-oxide formation reduces GM performance.

- ¹Stognei et al. Phys. Solid State **49**, 164 (2007)
- ²Niklasson et al. J. Appl. Phys. **55**, 3382 (1984)
- ³Barzilai et al. Phys. Rev. B **23**, 1809 (1981)
- ⁴Zhu et al. Phys. Rev. B **60**, 11918 (1999)
- ⁵Aronzon et al. Phys. Solid State **41**, 857 (1999)
- ⁶Honda et al. Phys. Rev. B **56**, 14566 (1997)
- ⁷Gittleman et al., Phys. Rev. B **5**, 3609 (1972)
- ⁸Toker et al. Phys. Rev. B **68**, 041403(R) (2003)
- ⁹Abeles et al. Adv. in Phys. **24**, 407 (1975)
- ¹⁰Milner et al. Phys. Rev. Lett. **76**, 475 (1996)
- ¹¹Abeles et al. Phys. Rev. Lett. **35**, 247 (1975)
- ¹²Wei et al. Appl. Phys. Lett. **102**, 131911 (2013)
- ¹³Balberg et al. Eur. Phys. J. B **86**, 428 (2013)
- ¹⁴Cohen et al., Phys. Rev. B **8**, 3689 (1973)
- ¹⁵Priestley et al. Phys. Rev. B **12**, 2121 (1975)
- ¹⁶McAlister et al. J. Phys. C: Solid State Phys. **17**, L751 (1984)

S.J. Gilbert et al., J. Phys. Condens. Matter **34**, 204007 (2022)

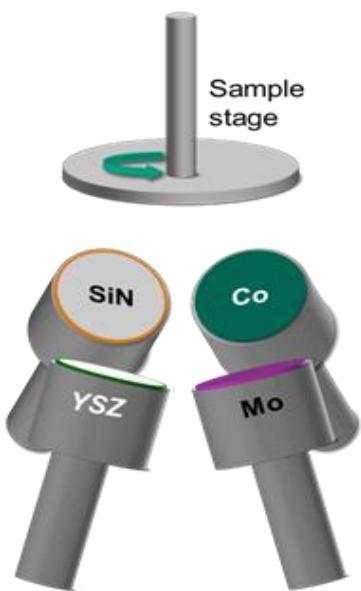
Reference	Metal	Insulator	$\Delta\sigma_{\varphi_c \pm 0.05}$
This work	Mo	YSZ	10^1
This work	Co	YSZ	10^1
Stognei ¹	Co	Al_2O_n	10^2
Barzilai ³	Co	SiO_2	10^2
Zhu ⁴	Fe	Al_2O_3	10^2
Aronzon ⁵	Fe	SiO_2	10^2
Honda ⁶	Fe	SiO_2	10^3
Gittleman ⁷	Ni	SiO_2	10^2
Toker ⁸	Ni	SiO_2	10^2
Abeles ⁹	Ni	SiO_2	10^2
Milner ¹⁰	Ni	SiO_2	10^4
Abeles ¹¹	W	Al_2O_3	10^2
Wei ¹²	Ag	SnO_2	10^1
Balberg ¹³	Ag	Al_2O_3	10^2
Cohen ¹⁴	Ag	SiO_2	10^4
Priestley ¹⁵	Ag	SiO_2	10^5
Abeles ⁹	Au	Al_2O_3	10^6
Cohen ¹⁴	Au	SiO_2	10^4
McAlister ¹⁶	Au	SiO_2	10^8

Conductivity change across percolation threshold.

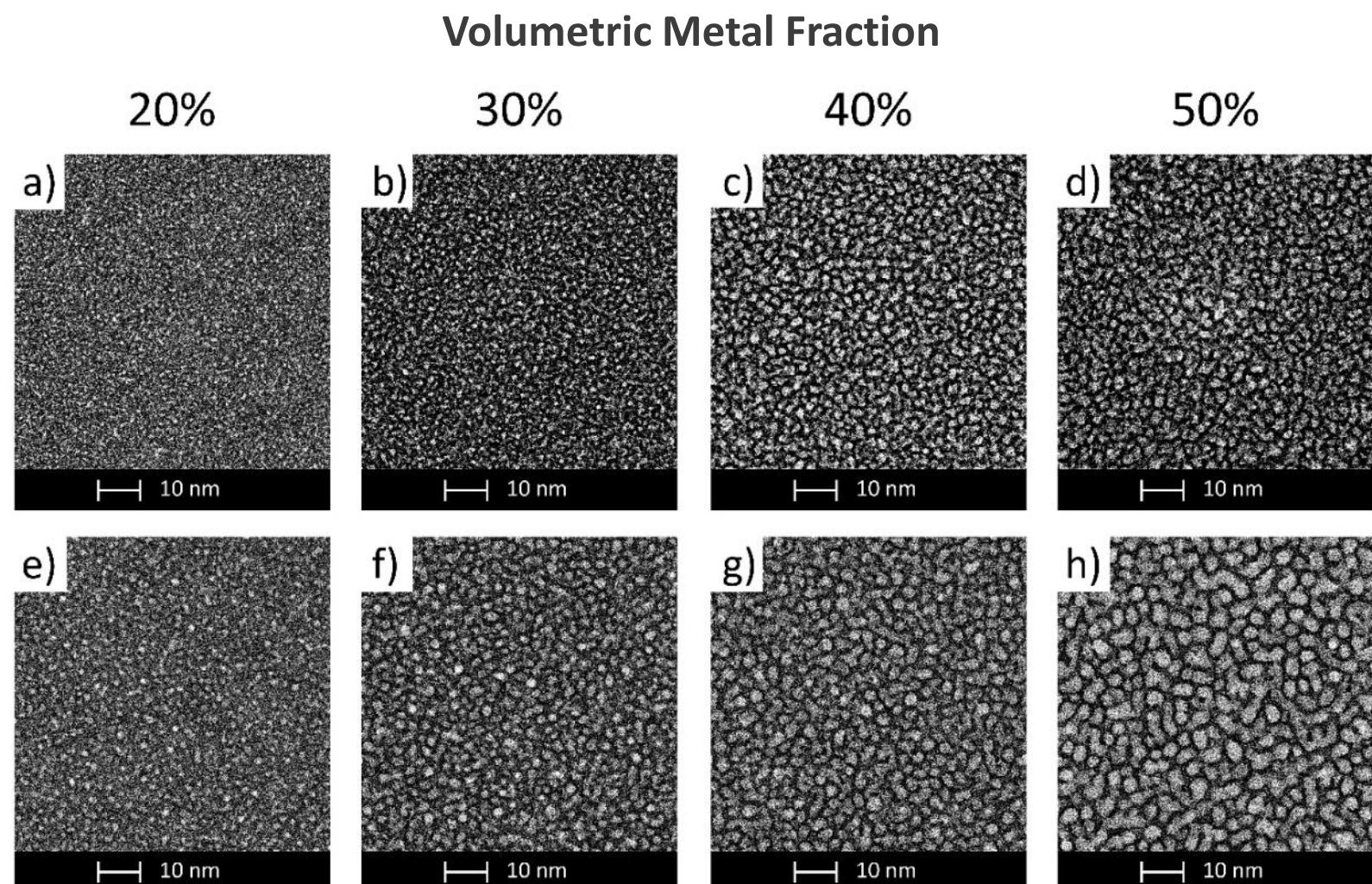
Non-noble metals typically 10^2 - 10^3

Noble metals typically $\geq 10^4$

Co-SiN_x and Mo-SiN_x GMs were synthesized by RF co-sputtering.



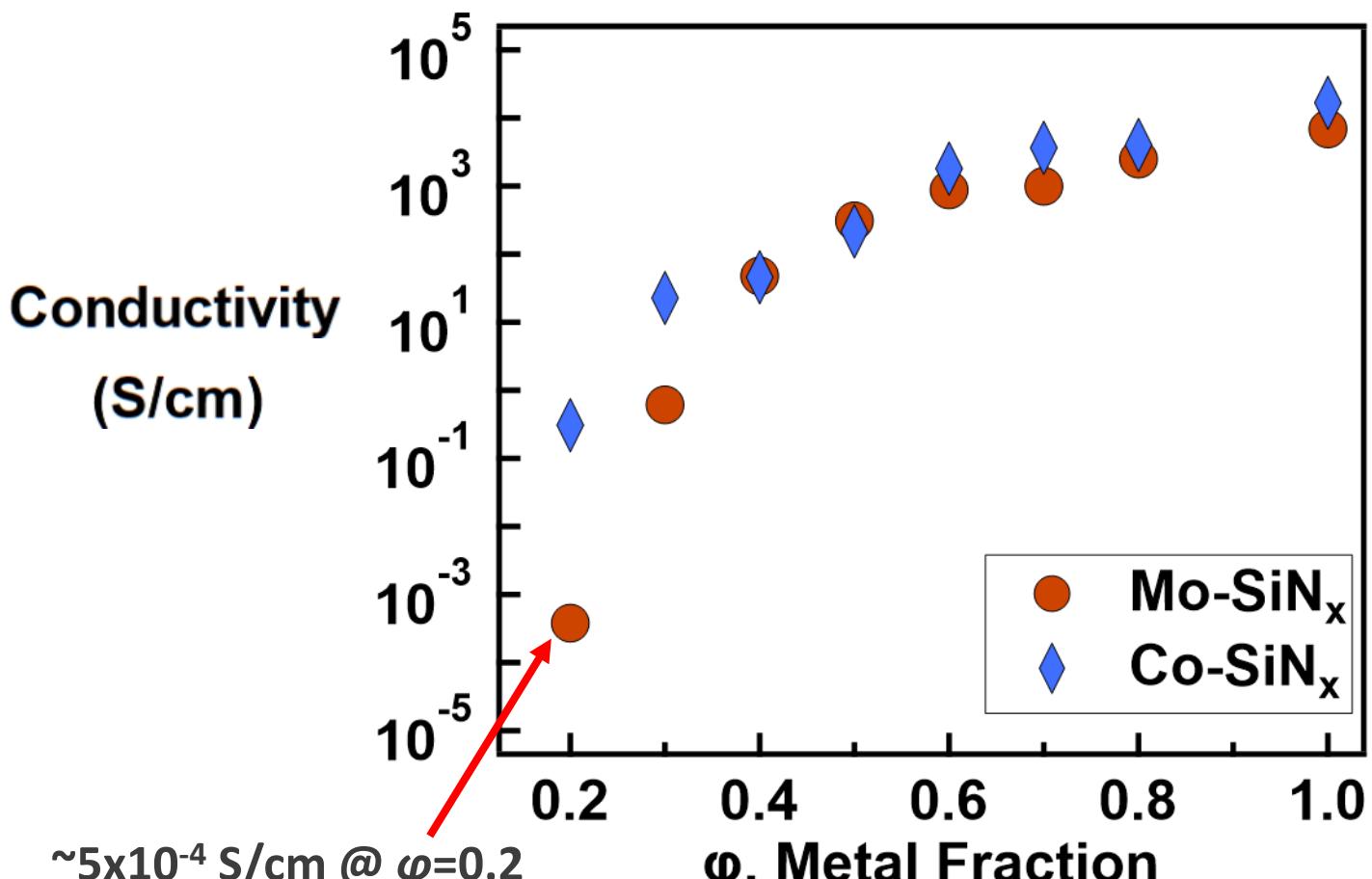
Mo-SiN_x



S.J. Gilbert et al., Nanotechnology, **34**, 415706 (2023)

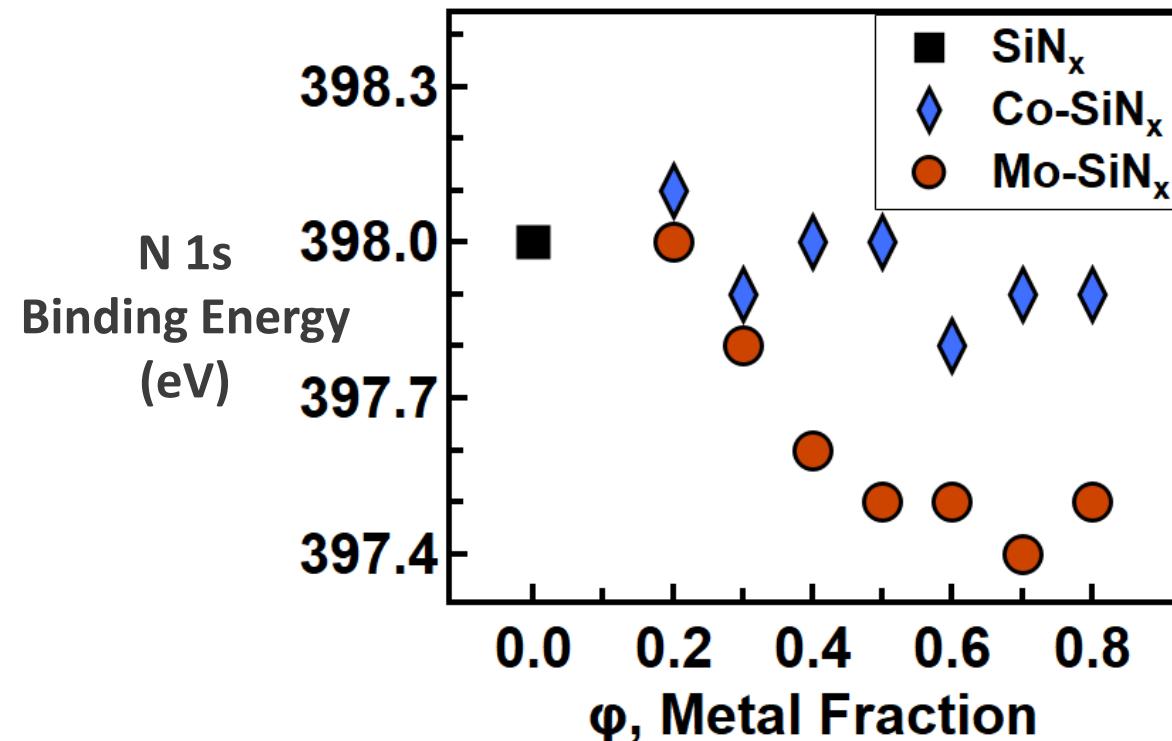
Nanoparticle diameters and separations are similar to YSZ GMs.

Conductivity still too high for electrical grid integration.



Target conductivity is 10^{-5} - 10^{-8} S/cm

Mo-SiN_x exhibits Mo-nitride formation.



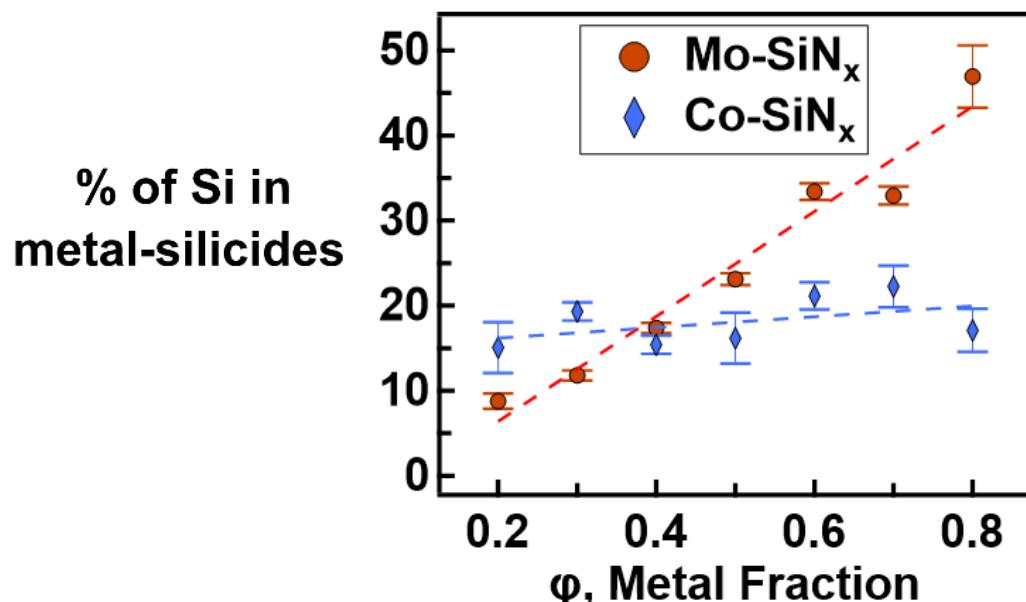
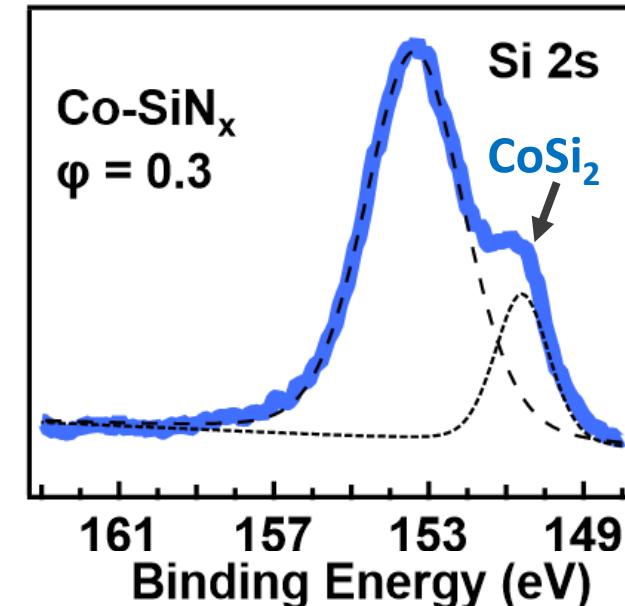
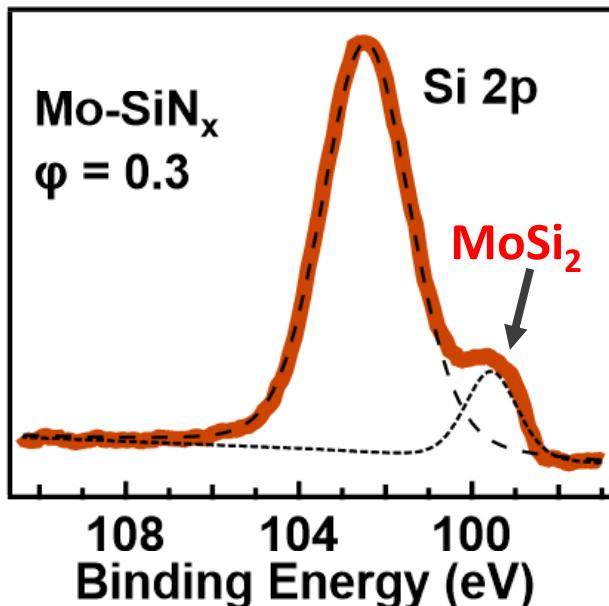
Group	Compound	ΔH (kJ*mol ⁻¹ *atom ⁻¹)	Reference
Mo-Nitrides	Mo ₂ N	-41	1
	MoN	-51	1
Co-Nitrides	Co ₄ N	+3	2
	Co ₂ N	-9	1
	CoN	0	1

S.J. Gilbert et al., Nanotechnology, **34**, 415706 (2023)

1. A. K. Niessen et al., Journal of the Less Common Metals **82**, 75-80 (1981).
2. I. K. Milad et al., Catalysis Letters **52**, 113-119 (1998).

Nitrogen vacancies cause metal-silicide formation and increase conductivity.

Normalized Intensity

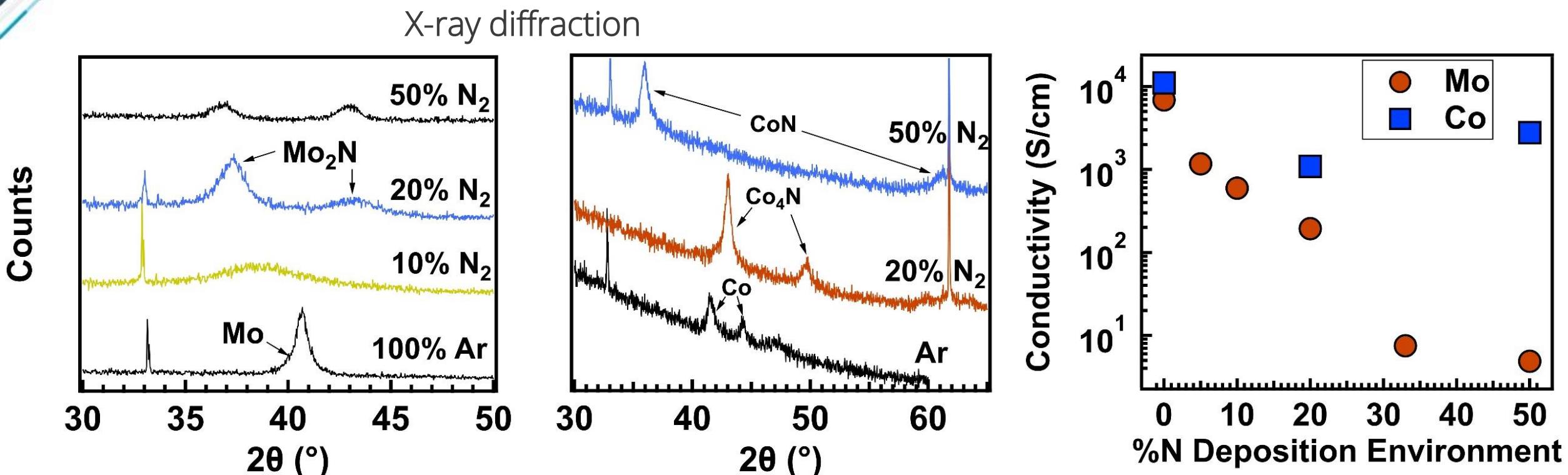


Target	Sputtering gas	$\rho_{(300K)}$ ($\Omega \text{ cm}$)
β -Si ₃ N ₄	100%Ar	1.7×10^{10}
	80%Ar-20N ₂	1.1×10^{11}
	50%Ar-50N ₂	3.4×10^{14}
	20%Ar-80N ₂	1.3×10^{13}
	100N ₂	6.2×10^{12}

Vila et al. Thin Solid Films 459, 195 (2004)

Insulator can be repaired by depositing in Ar/N₂.

Sputtering metals in N_2 results in metal-nitrides.



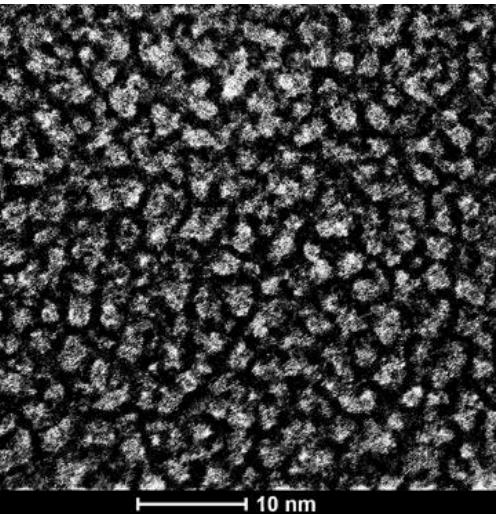
Selected environments

Mo-SiN_x: 10% N_2

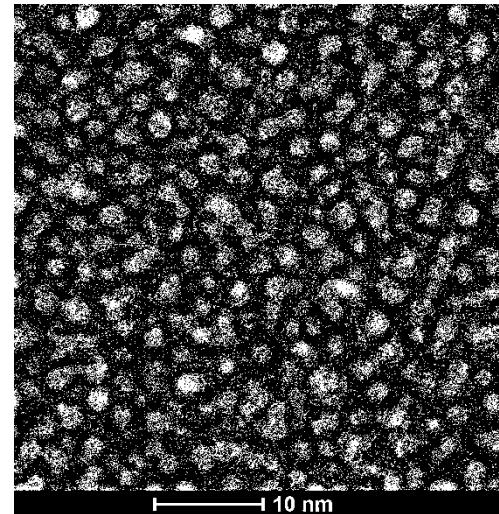
Co-SiN_x: 50% N_2

Deposition in N_2 Reduces Nanoparticle Size

Mo-SiN_x ($\phi=0.5$)

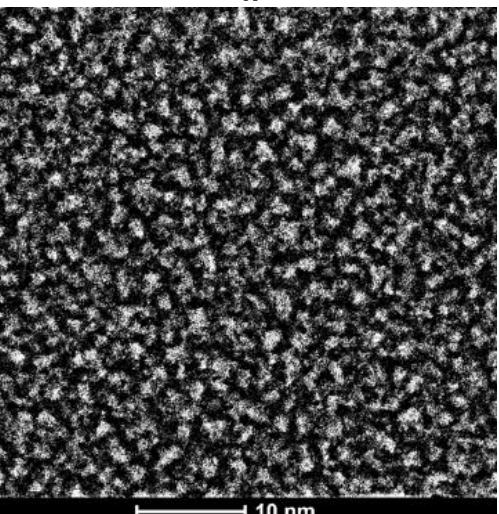


Co-SiN_x ($\phi=0.3$)



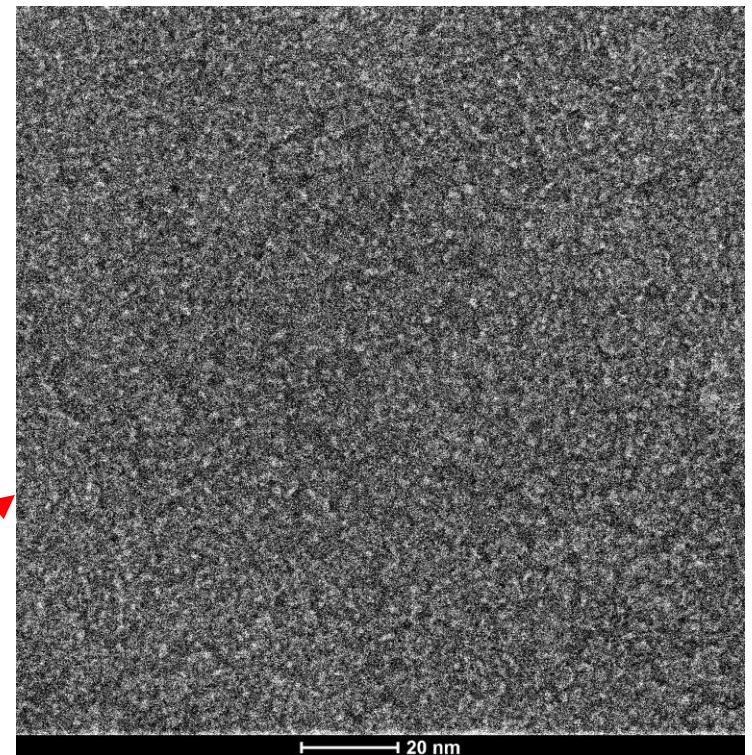
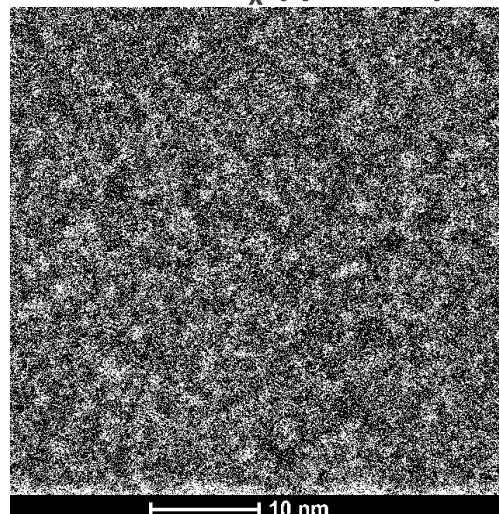
100% Ar

Mo-SiN_x ($\phi=0.5$)



10% N_2

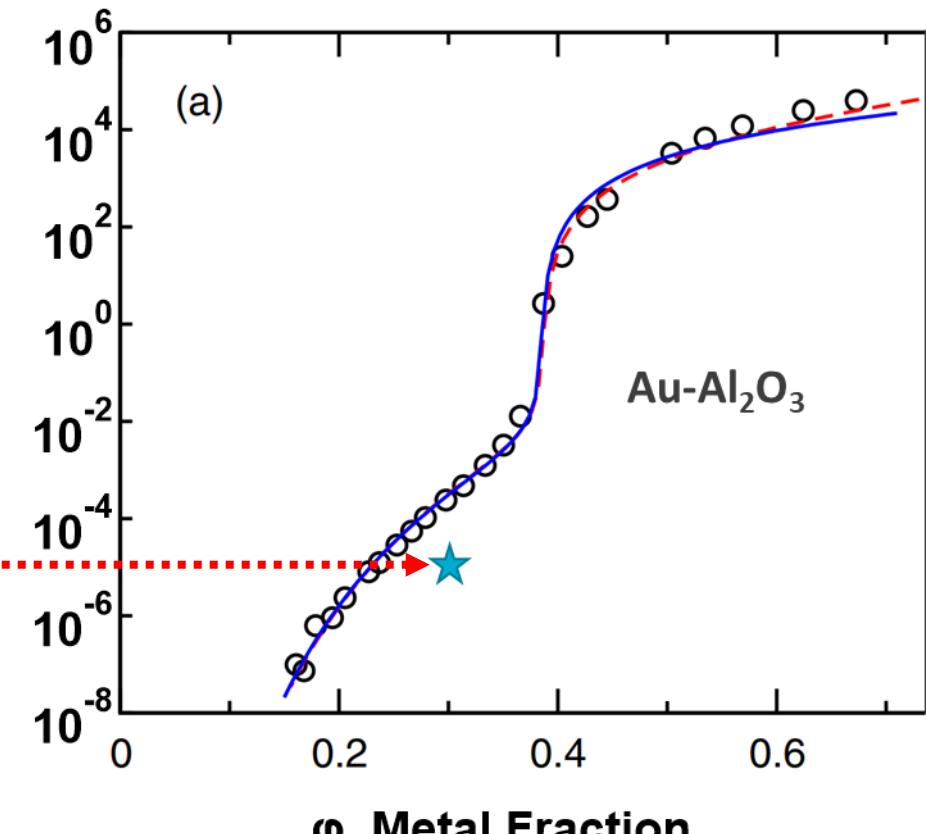
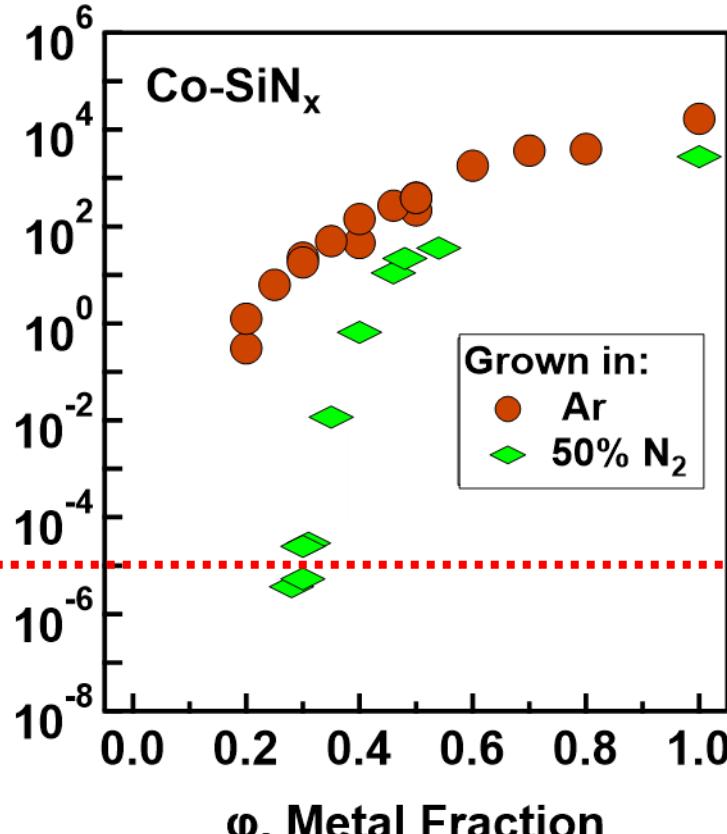
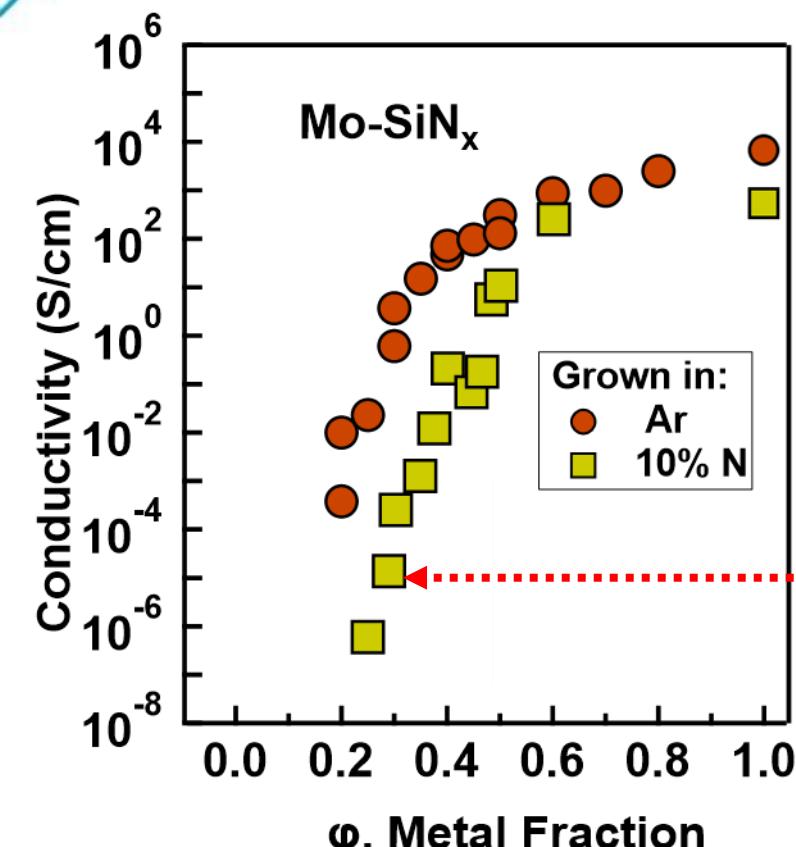
Co-SiN_x ($\phi=0.35$)



M. McGarry et al., submitted

S.J. Gilbert et al., in progress

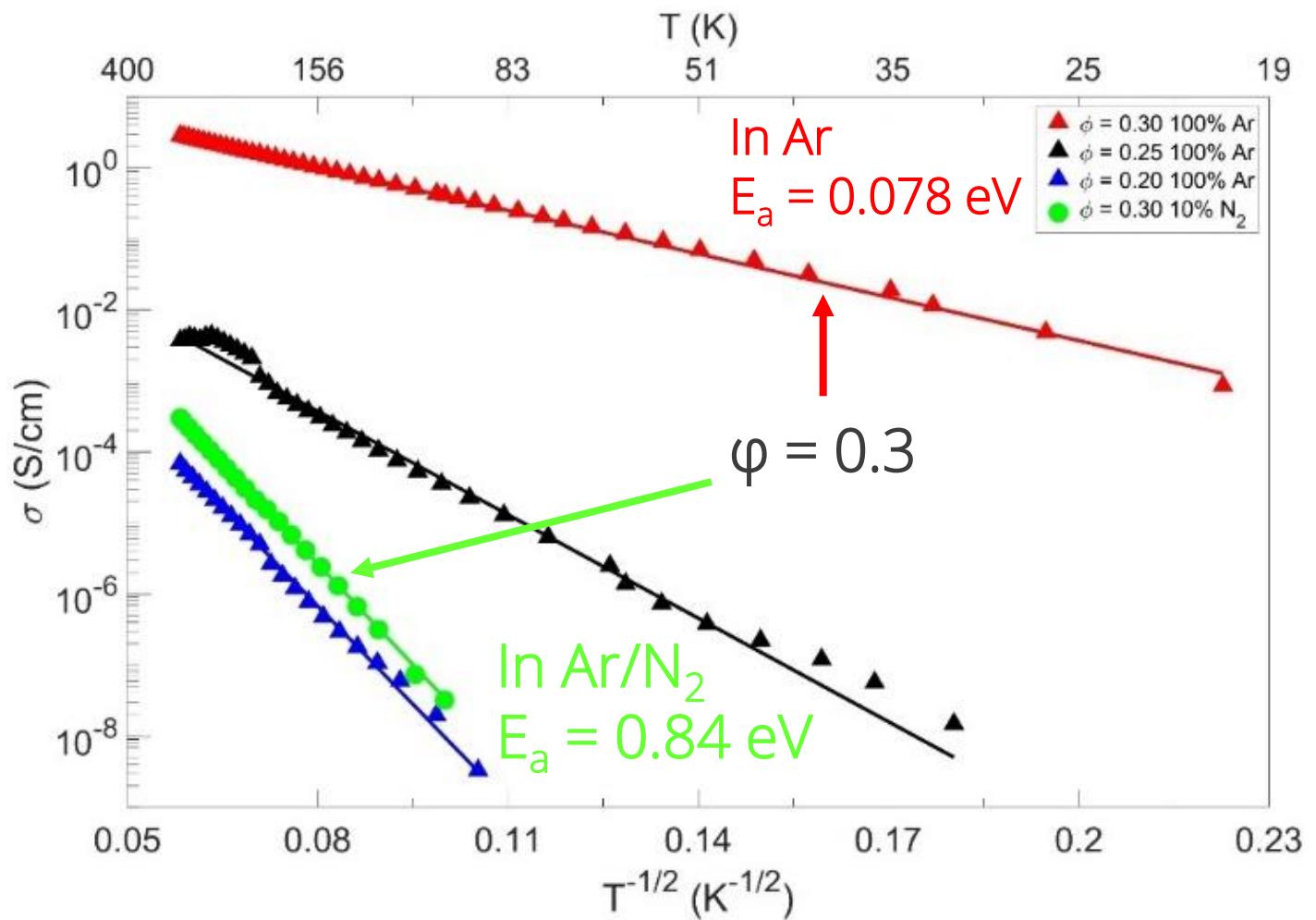
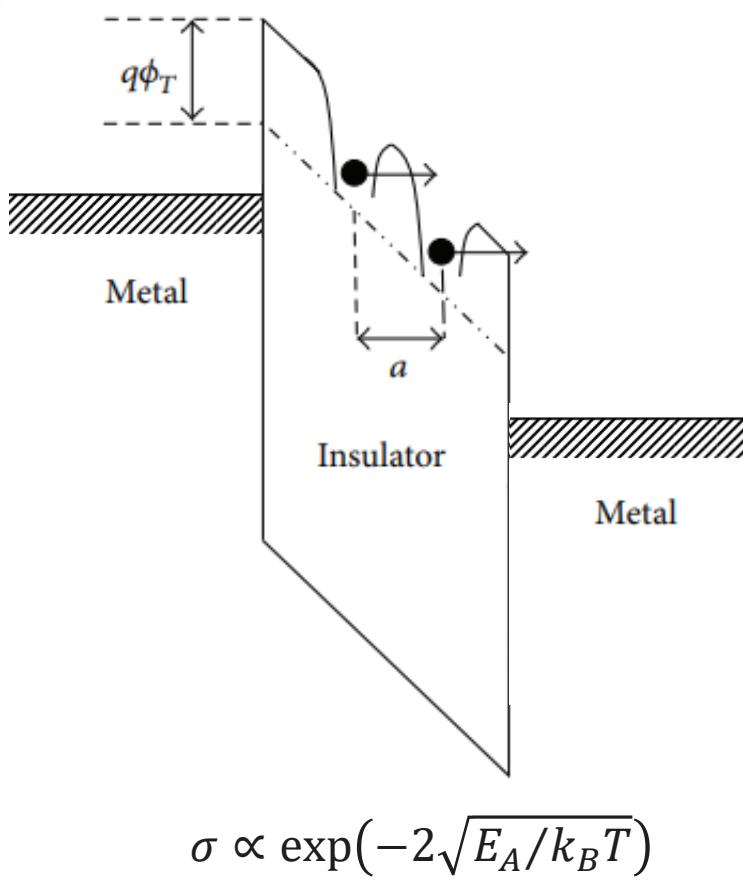
Significant insulator improvements when deposited N_2



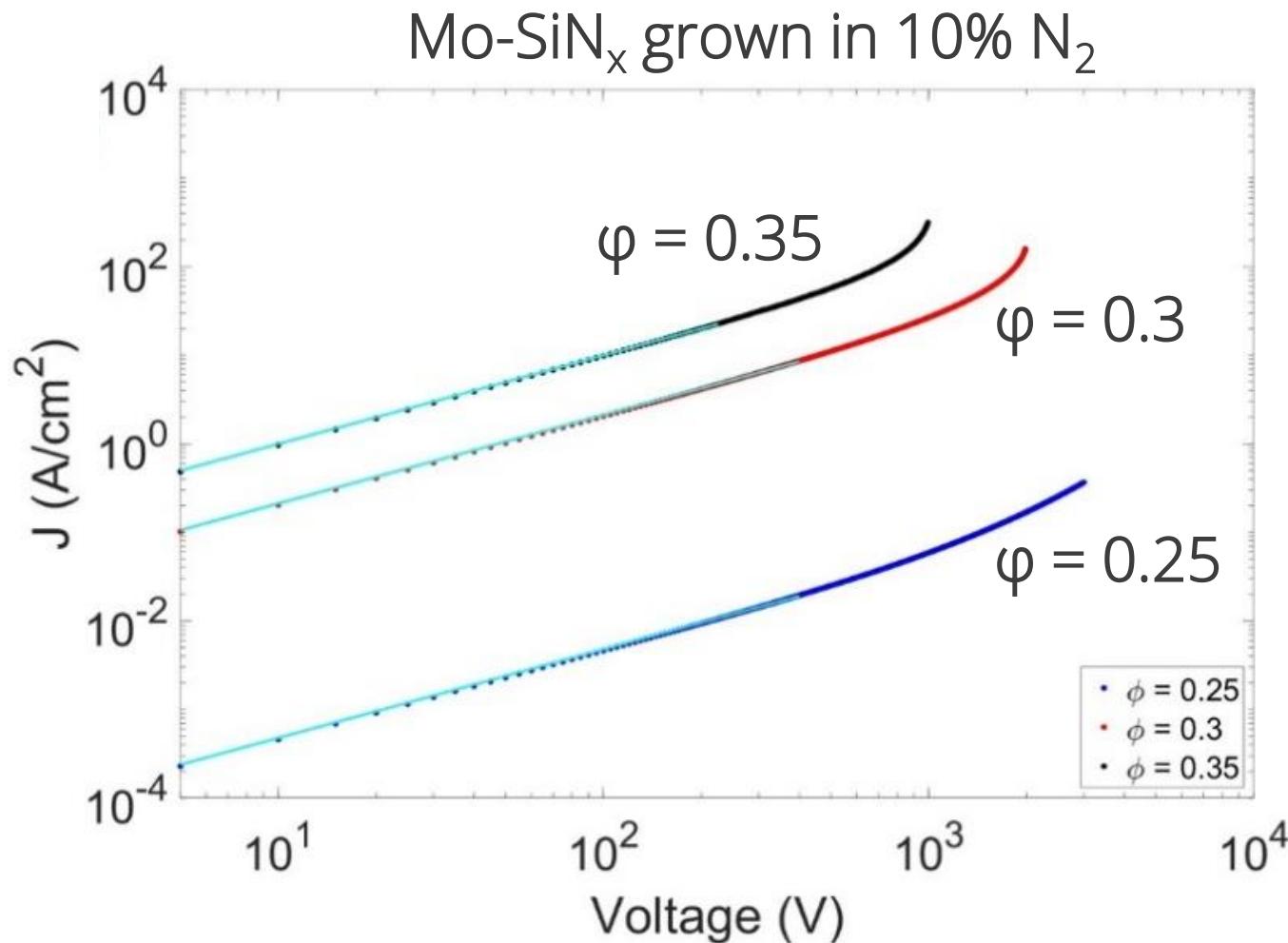
Low conductivities previously only seen with noble metals.

Deposition in N_2 greatly increases activation energy

Hopping Conduction



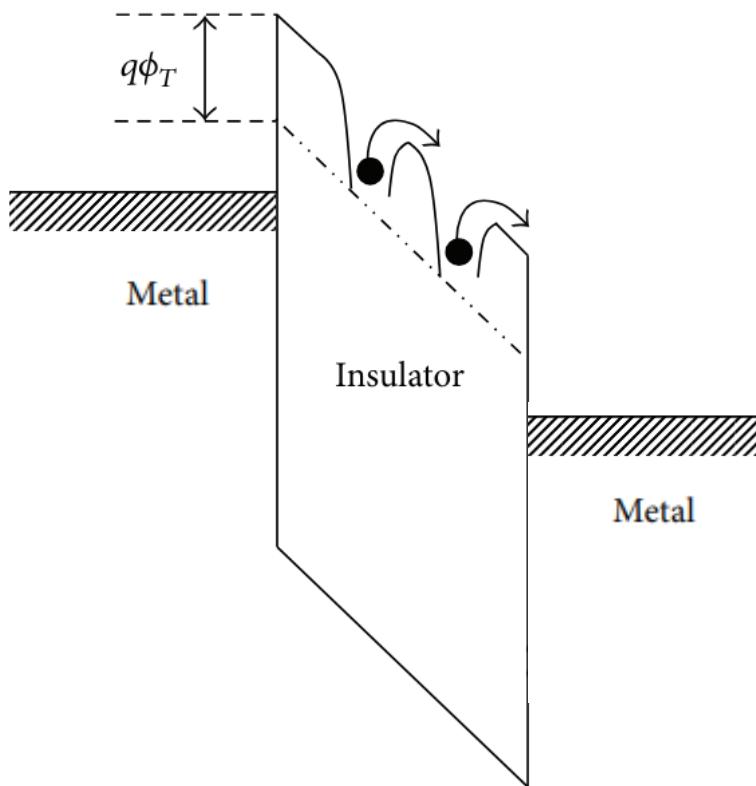
Field enhanced tunneling is observed at higher electric fields



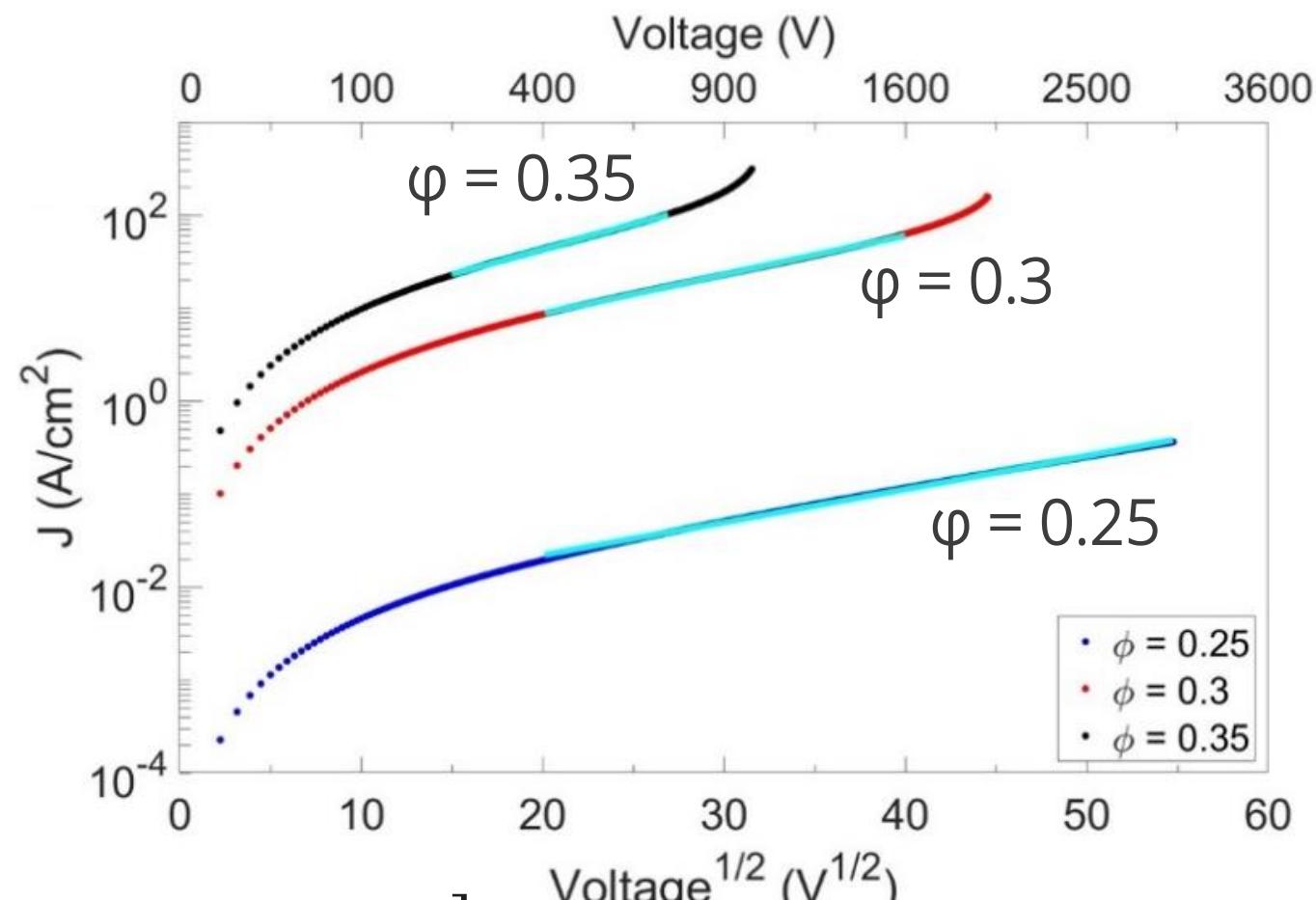
Ohmic conduction up to \sim 20 kV/cm

Poole-Frenkel emission for electric fields >20 kV/cm

Poole-Frenkel Emission



Mo-SiN_x grown in 10% N₂

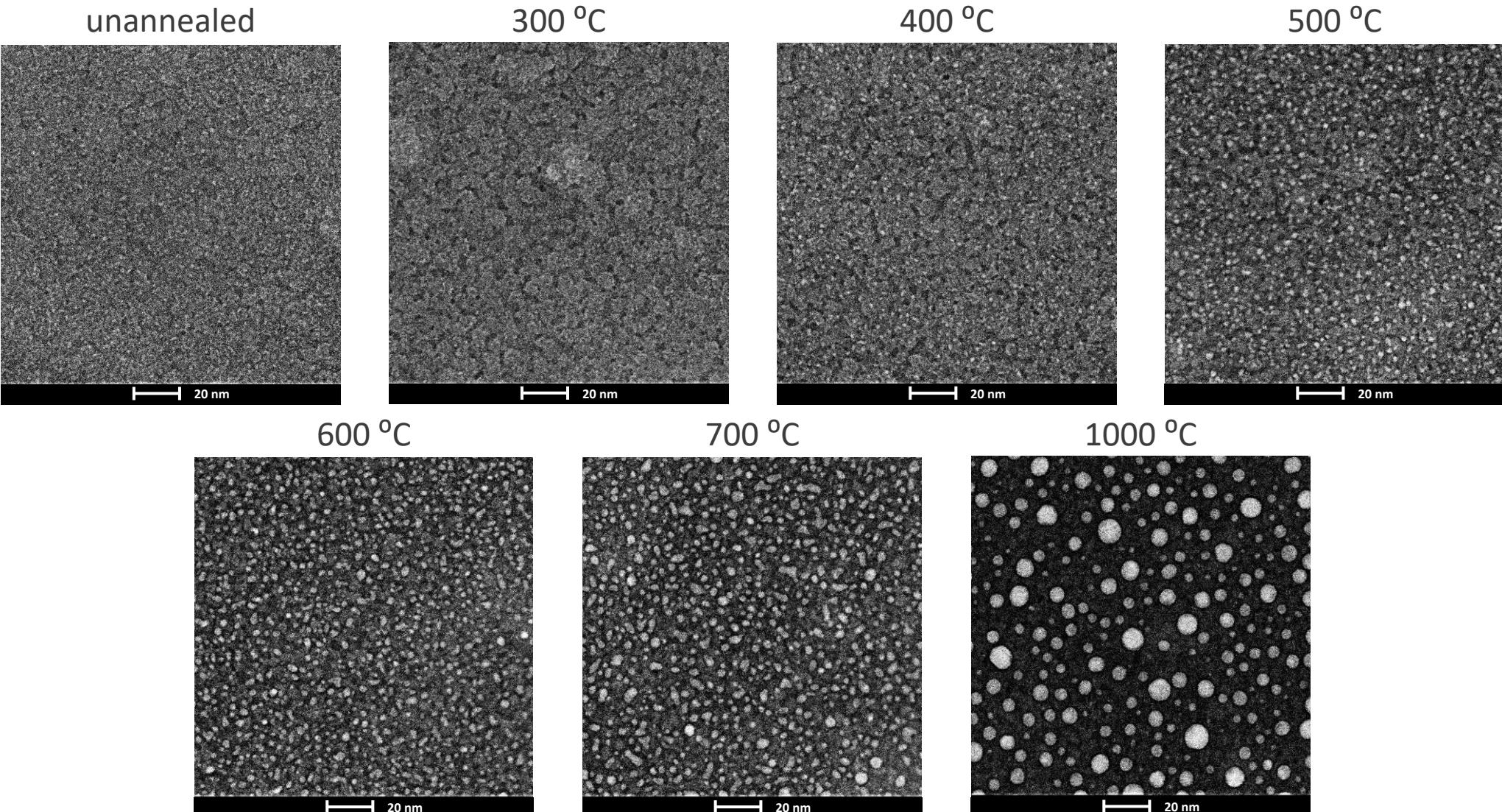


$$\sigma \propto \exp \left[(q/k_B T) \sqrt{qE/\epsilon_0 \epsilon_r} \right]$$

Maximum voltage limited by equipment NOT material.

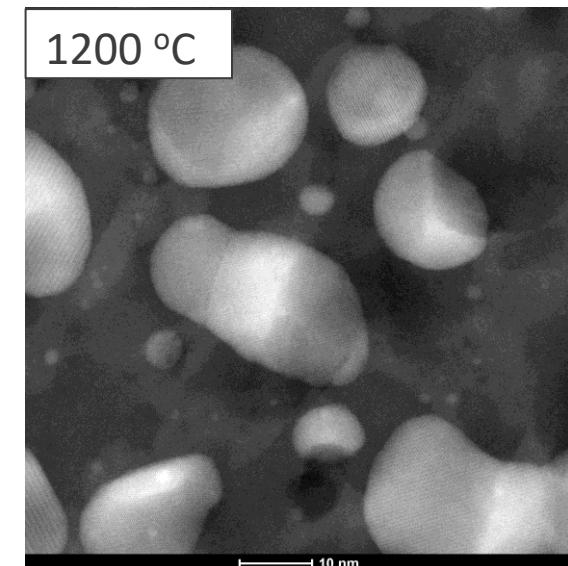
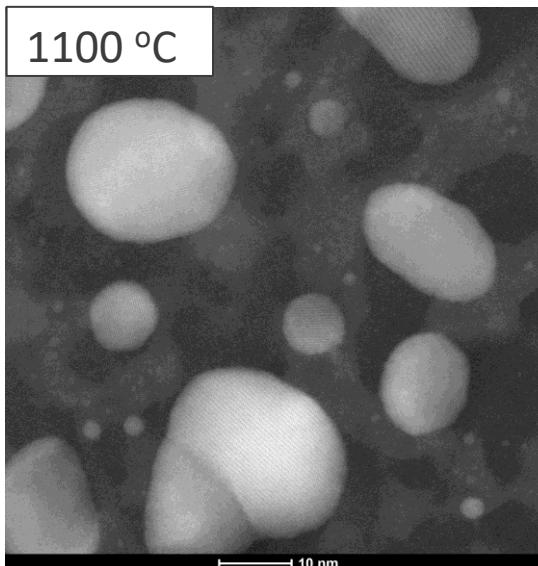
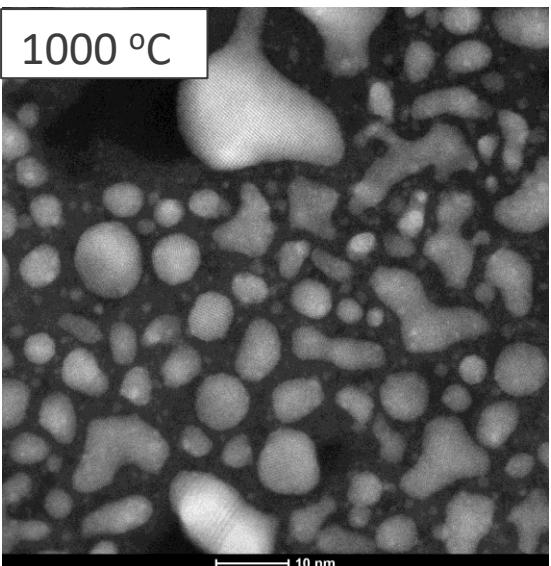
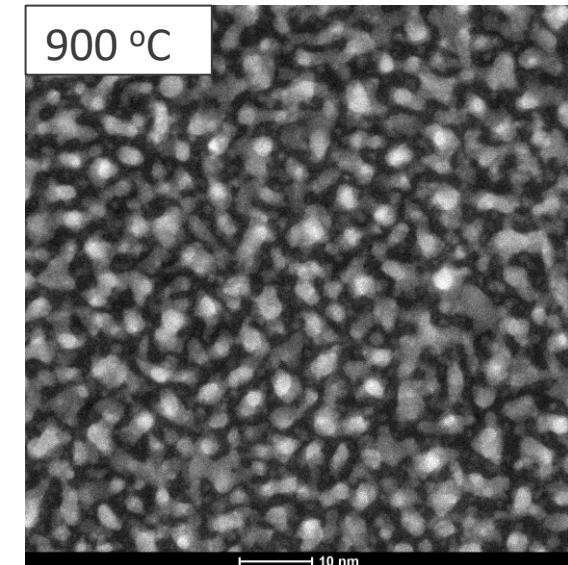
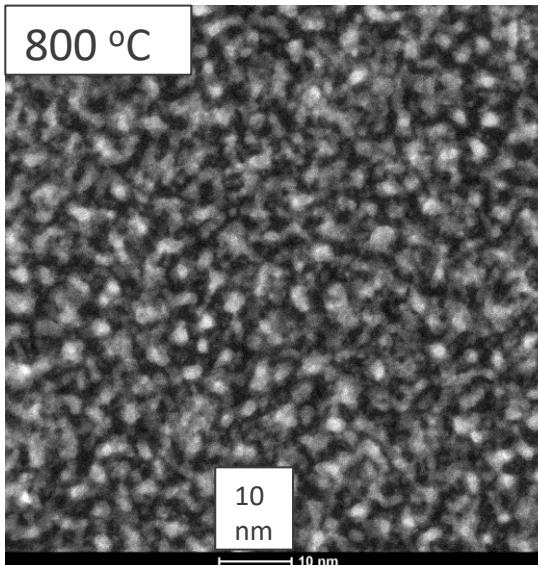
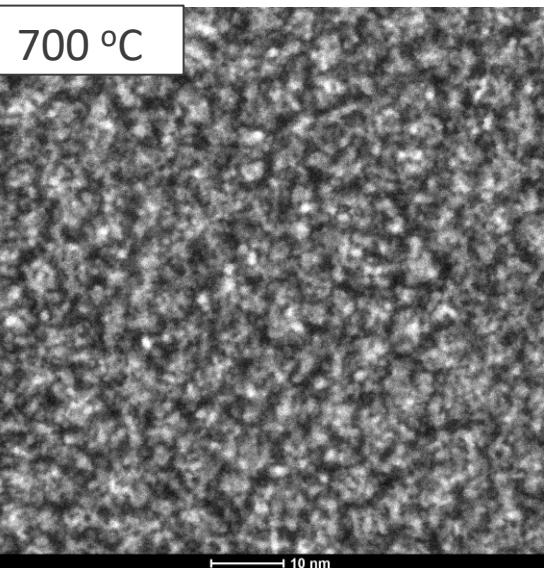
Annealing Increases Nanoparticle Size and Separation

Co-SiN_x grown in 50% N₂ ($\phi=0.35$)

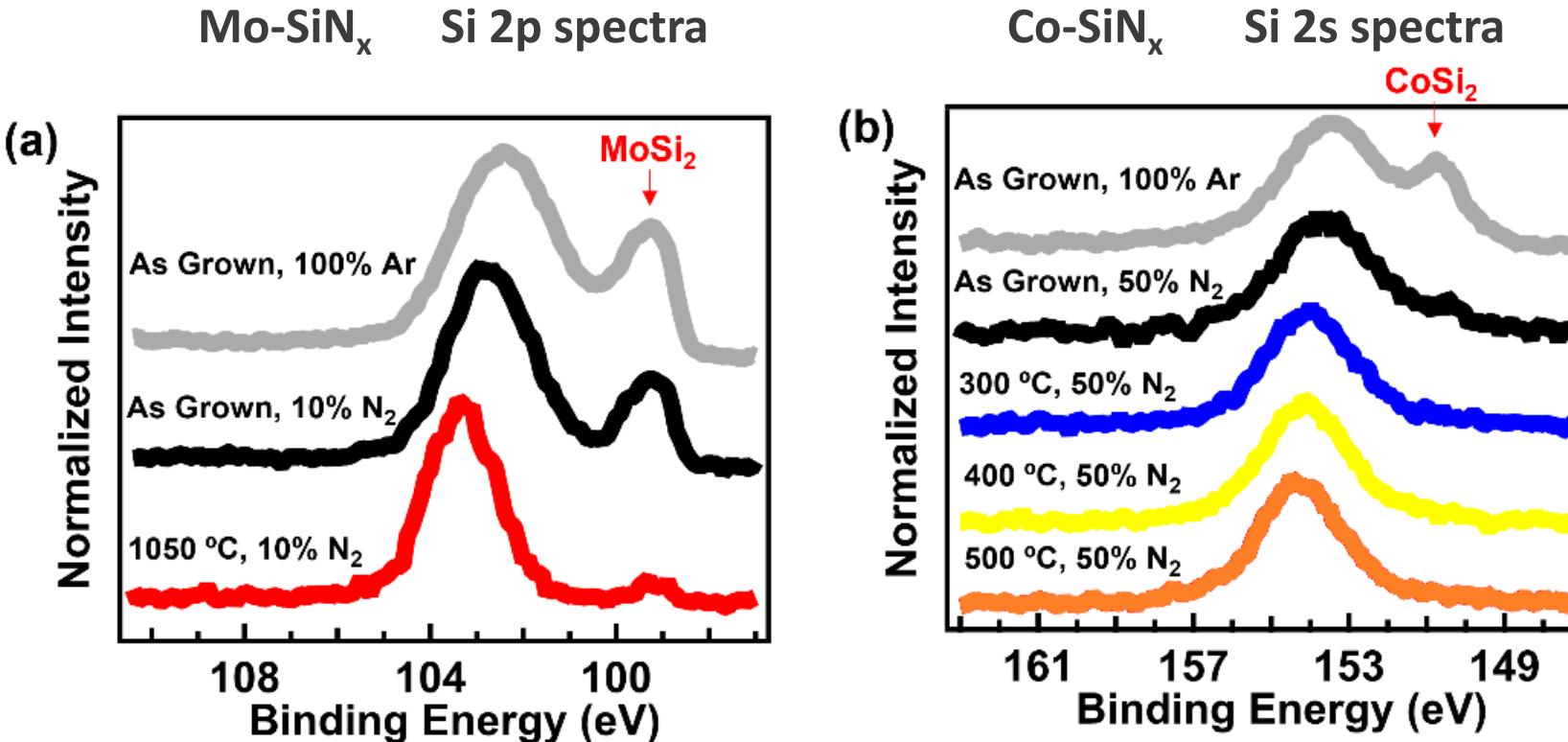


Mo-SiN_x is stable up to ~800 °C

Mo-SiN_x grown in 10% N₂ ($\phi=0.4$)



Deposition in N_2 and Annealing Reduce Metal-Silicide Content

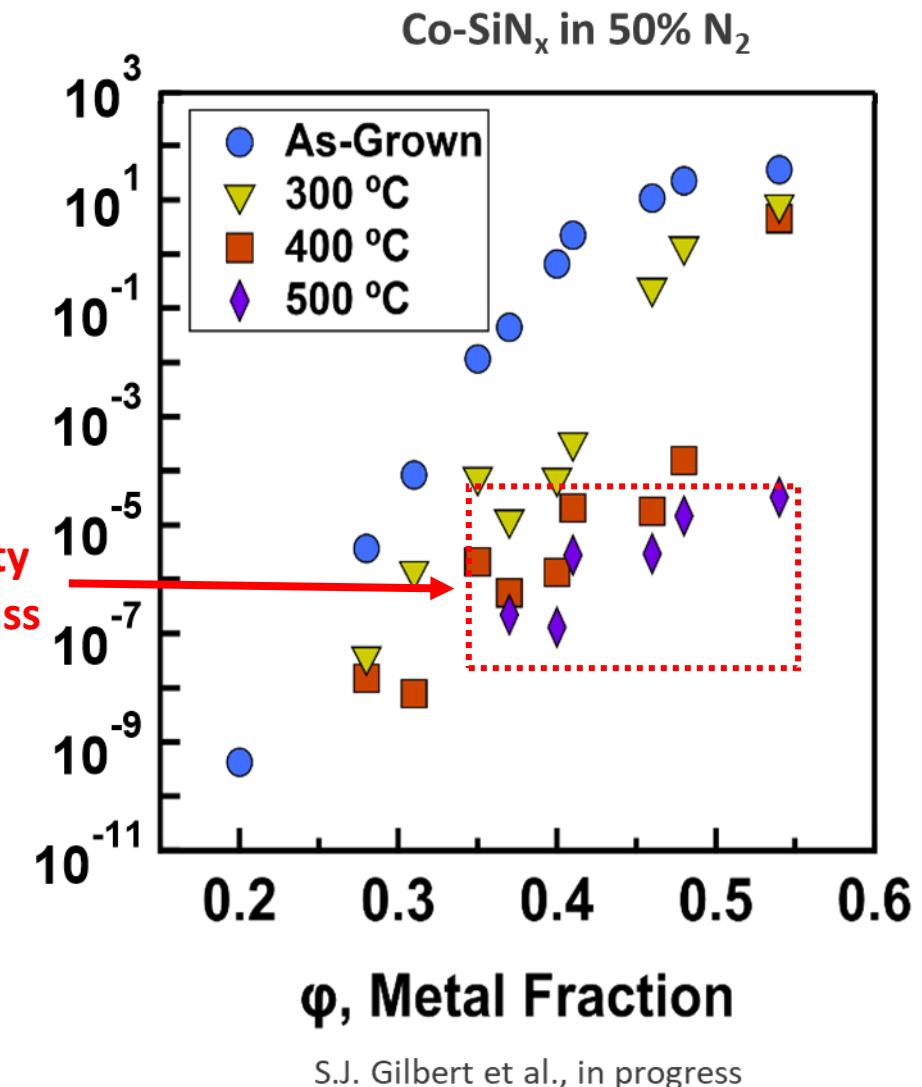
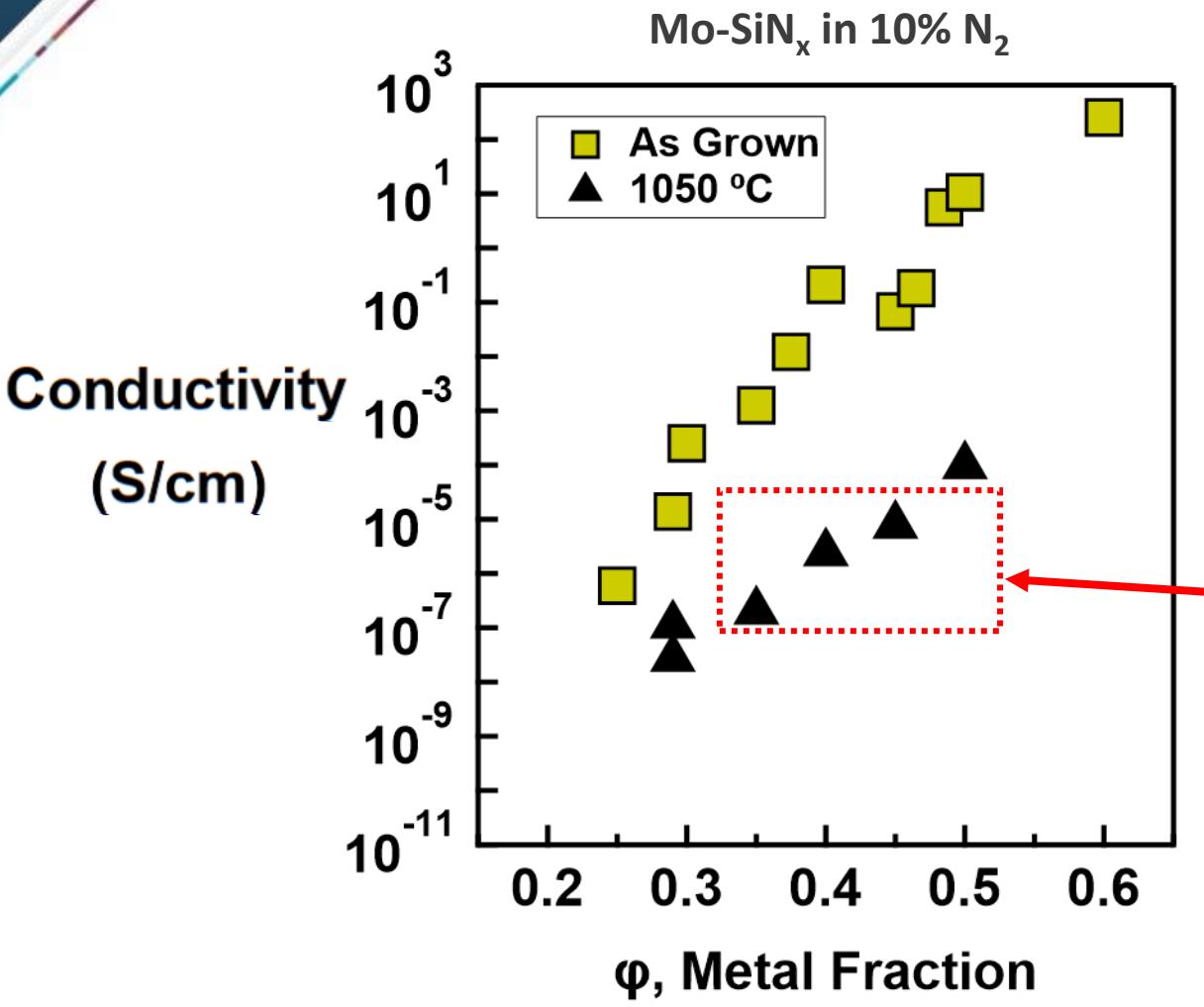


S.J. Gilbert et al., in progress

Group	Compound	$\Delta_f H$ (kJ*mol ⁻¹ *atom ⁻¹)	Ref.
Silicon nitride	Si_3N_4	-118	1
Mo-silicides	Mo_3Si	-31	2
	Mo_5Si_3	-39	3
	$MoSi_2$	-46	4
Co-silicides	Co_2Si	-41	5
	$CoSi$	-48	5
	$CoSi_2$	-33	5

1. P. A. G. O'Hare et al., The Journal of Chemical Thermodynamics **31** (3), 303-322 (1999).
2. I. Tomaszkiewicz et al., The Journal of Chemical Thermodynamics **28** (1), 29-42 (1996).
3. I. Tomaszkiewicz et al., The Journal of Chemical Thermodynamics **29** (1), 87-98 (1997).
4. P. A. G. O'Hare et al., The Journal of Chemical Thermodynamics **25** (11), 1333-1343 (1993).
5. D. Lexa et al., Chemistry of Materials **8** (11), 2636-2642 (1996).

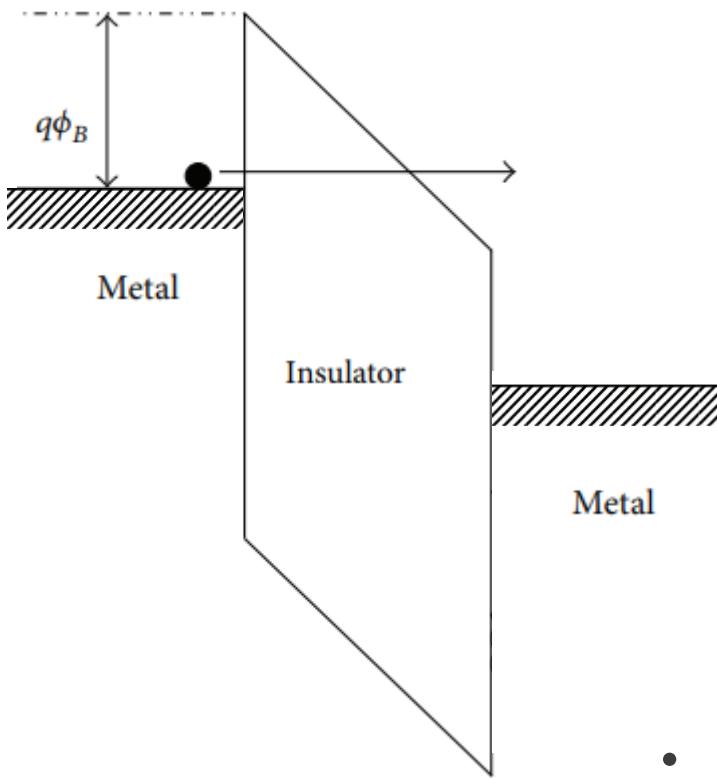
Annealing further improves insulator quality.



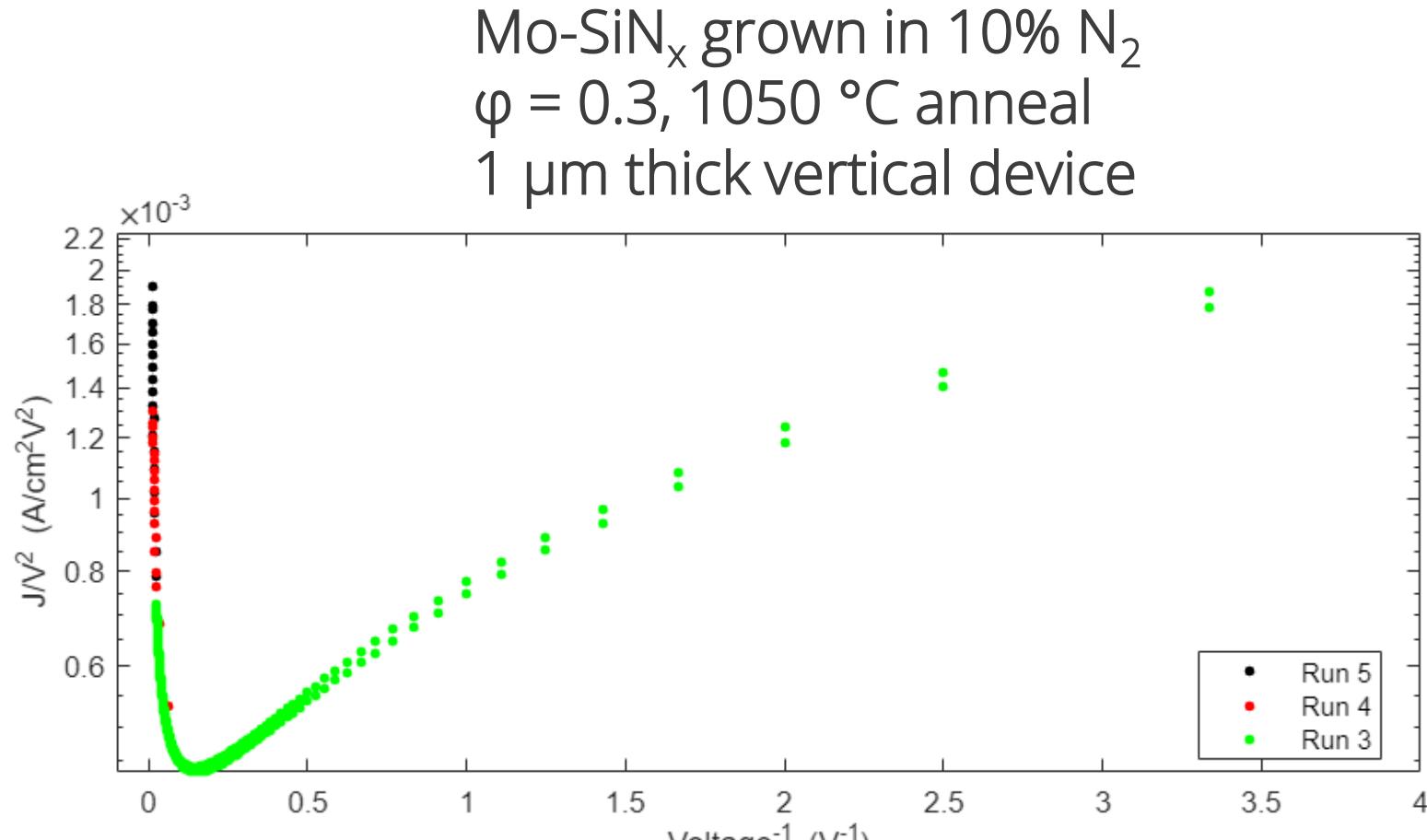
Potential protection devices with $\geq 50\%$ metal fraction.

Fowler-Nordheim tunneling enhances current carrying capacity

Fowler-Nordheim Tunneling



$$\sigma \propto E^2 \exp(E_0/E)$$



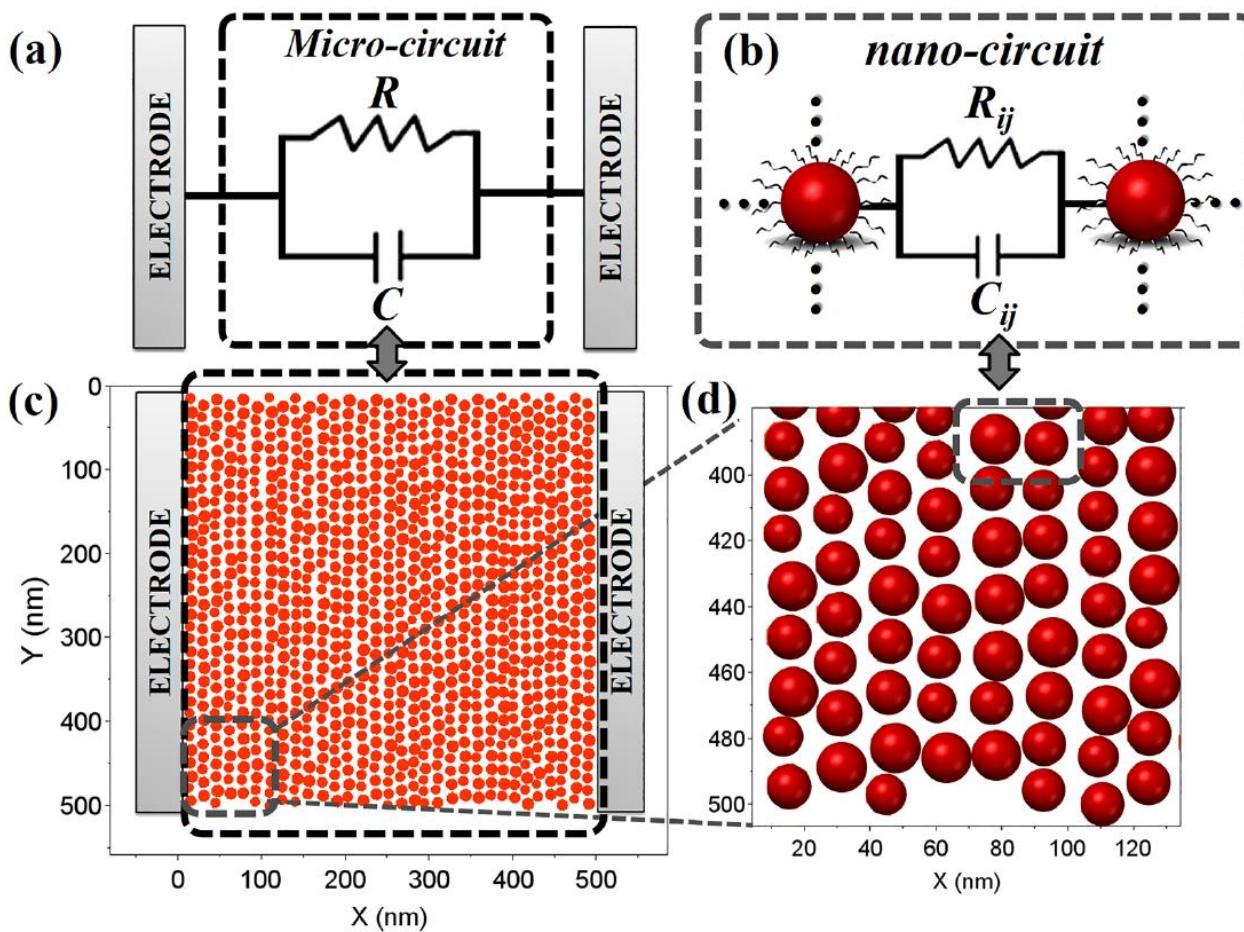
M. McGarry et al., in progress

- High breakdown strength (>0.8 MV/cm) allows for compact devices.
- Current densities measured up to 10 A/cm².

High frequencies also enhance GM conductivity.

Complementary tunneling and capacitive conduction paths.

GMs follow Jonscher's universal power law



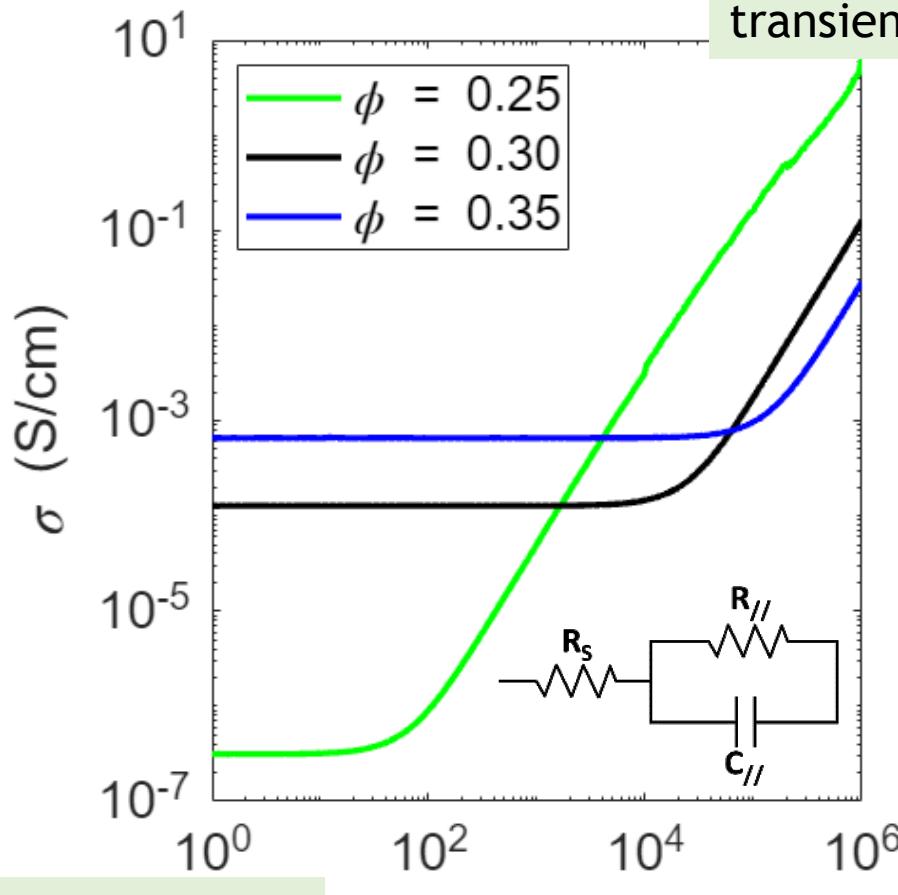
$$\sigma_{AC}'(\omega) = \sigma_{DC} + A\omega^n$$

Tunneling dominates at low frequencies.

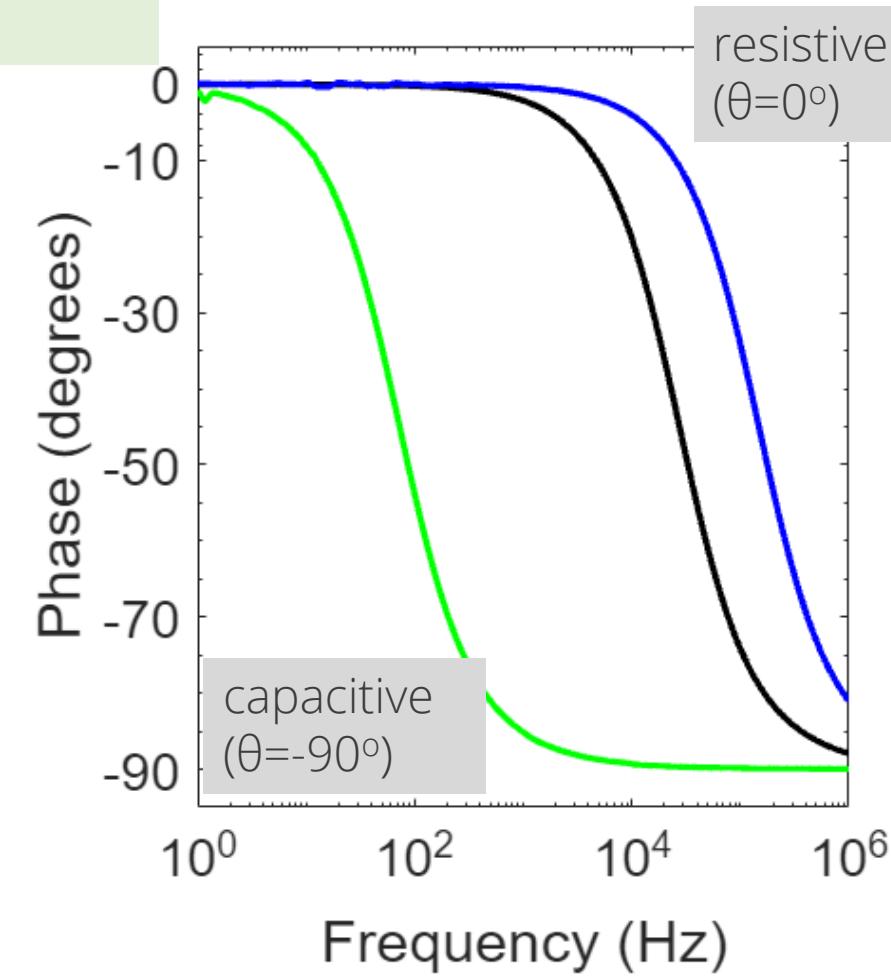
Capacitive transport dominates at high frequencies.

Material advances result in extraordinarily σ_{AC} response

Mo-SiN_x grown in 10% N₂



High $\sigma(\omega)$ at MHz
→ Shunt ns
transients



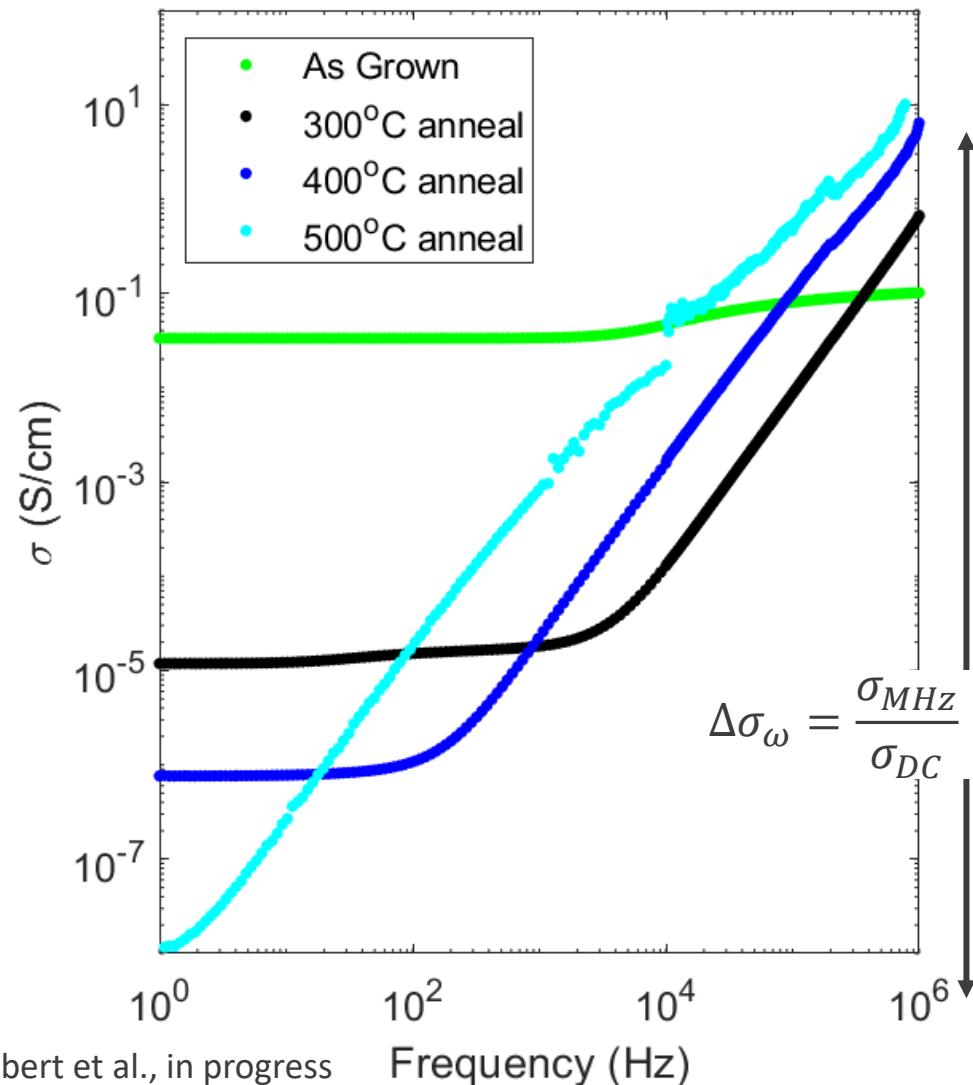
Low $\sigma(\omega)$ at 60 Hz
→ Negligible
leakage current

Frequency (Hz)

M. McGarry et al., submitted

Material advances result in extraordinarily σ_{AC} response

Co-SiN_x, grown in 50% N₂, $\varphi = 0.4$



GM	Annealing	φ	$\Delta\sigma_\omega$
<i>Literature</i>			
Pd-ZrO ₂ [1]	As Grown	0.28	50
(FeCoZr) _x (PZT) _(100-x) [2]	As Grown	0.52	100
Pt-SiO ₂ [3]	As Grown	0.3-0.6	10 ³ – 10 ⁴
<i>This LRD</i>			
Mo-SiN _x , 10% N ₂	As Grown	0.35	40
Mo-SiN _x , 10% N ₂	As Grown	0.30	10 ³
Mo-SiN _x , 10% N ₂	As Grown	0.25	10 ⁷
Mo-SiN _x , 10% N ₂	1050 °C	0.29	10 ⁸
Co-SiN _x , 50% N ₂	As Grown	0.4	<10
Co-SiN _x , 50% N ₂	300 °C	0.4	10 ⁵
Co-SiN _x , 50% N ₂	400 °C	0.4	10 ⁷
Co-SiN _x , 50% N ₂	500 °C	0.4	10 ⁹

1. H. Bakkali et al., Sci. Rep. **6**, 29676 (2016).

2. O. Boiko et al., AIP Advances **12** (2), 025306 (2022).

3. N. Moyo and K. Leaver, J. Phys. D: Appl. Phys. **13** (8), 1511 (1980).

Conclusion: Granular Metals are promising for nanosecond high voltage transient protection

- ✓ compact
 - >1 MV/cm breakdown strength
- ✓ insulating at 60 Hz and low electric fields
 - Conductivities of 10^{-5} - 10^{-7} S/cm
- ✓ high thermal stability
 - Mo-SiN_x stable to ~800 °C
- ✓ conducting for 1 GHz voltage spikes
 - > 10^6 conductivity increase at 1 MHz
- ?□ large current carrying capacity (>1 kA/cm²)
 - Coupled high frequency/electric-field measurements needed.

sjgilbe@sandia.gov